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(54) **NEGATIVE GATE STRESS OPERATION IN MULTI-PASS PROGRAMMING AND MEMORY DEVICE THEREOF**

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(52) **U.S. Cl.**
CPC *GIIC 16/3459* (2013.01); *GIIC 16/3404* (2013.01); *GIIC 16/102* (2013.01); *GIIC 16/26* (2013.01); *GIIC 16/08* (2013.01); *GIIC 16/24* (2013.01); *GIIC 16/30* (2013.01); *GIIC 16/0433* (2013.01)

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(57) **ABSTRACT**

(21) Appl. No.: **17/232,059**

A memory device is provided. The memory device includes an array of memory cells arranged, a plurality of word lines, and a peripheral circuit configured to perform multi-pass programming on a selected row of memory cells coupled to a selected word line. The multi-pass programming includes a plurality of programming passes. Each of the programming passes includes a programming operation and a verify operation. To perform the multi-pass programming, the peripheral circuit is configured to, in a non-last programming pass of memory cells, perform a negative gate stress (NGS) operation on a memory cell in the selected row of memory cells between the programming operation and the verify operation; and at a same time, perform a NGS operation on a memory cell in an unselected row of memory cells coupled to an unselected word line of the word lines. The unselected word line is adjacent to the selected word line.

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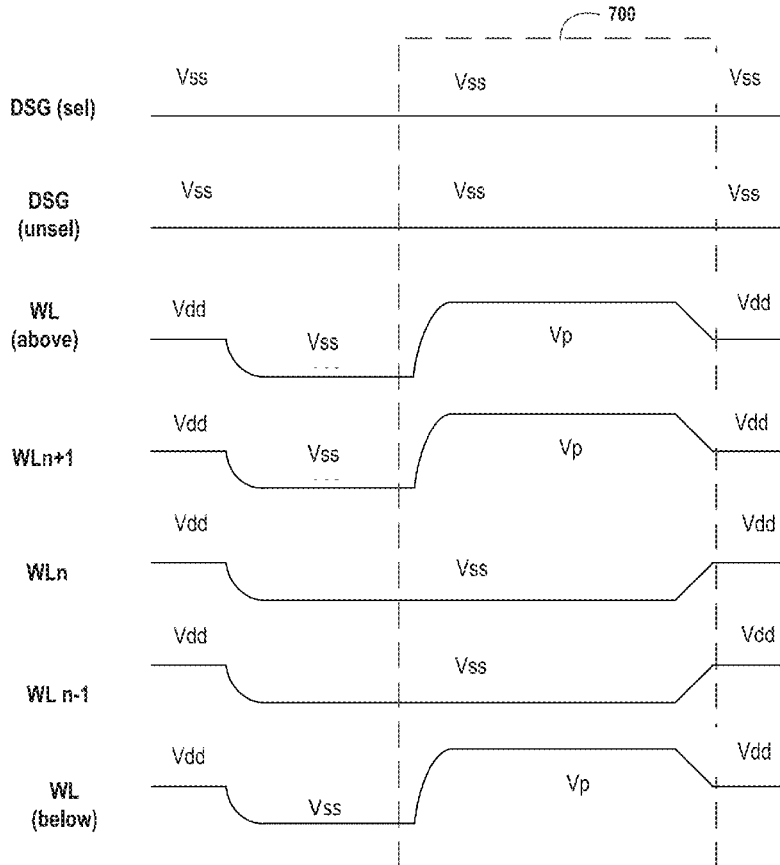
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100

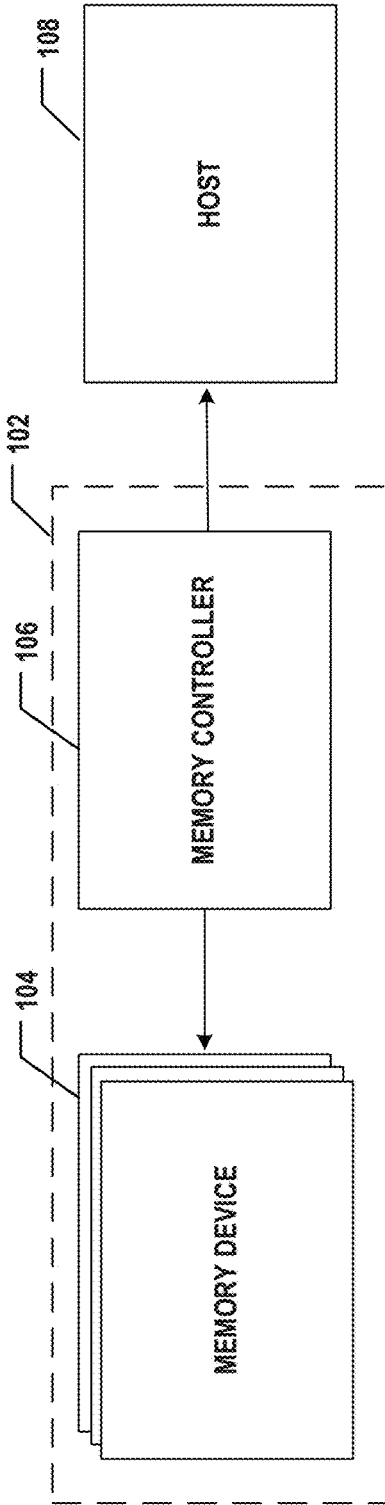


FIG. 1A

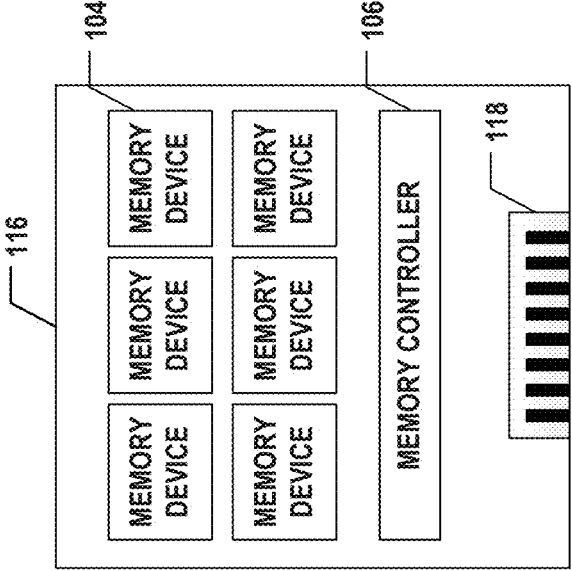


FIG. 1B

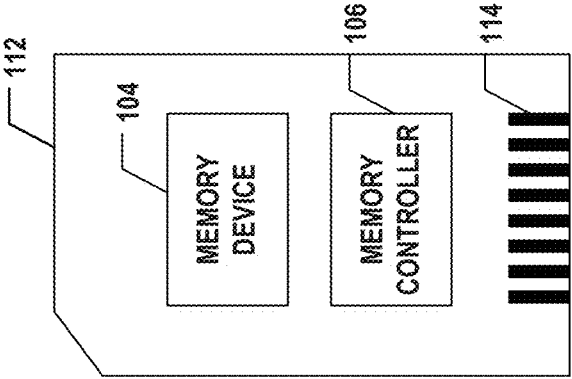


FIG. 1C

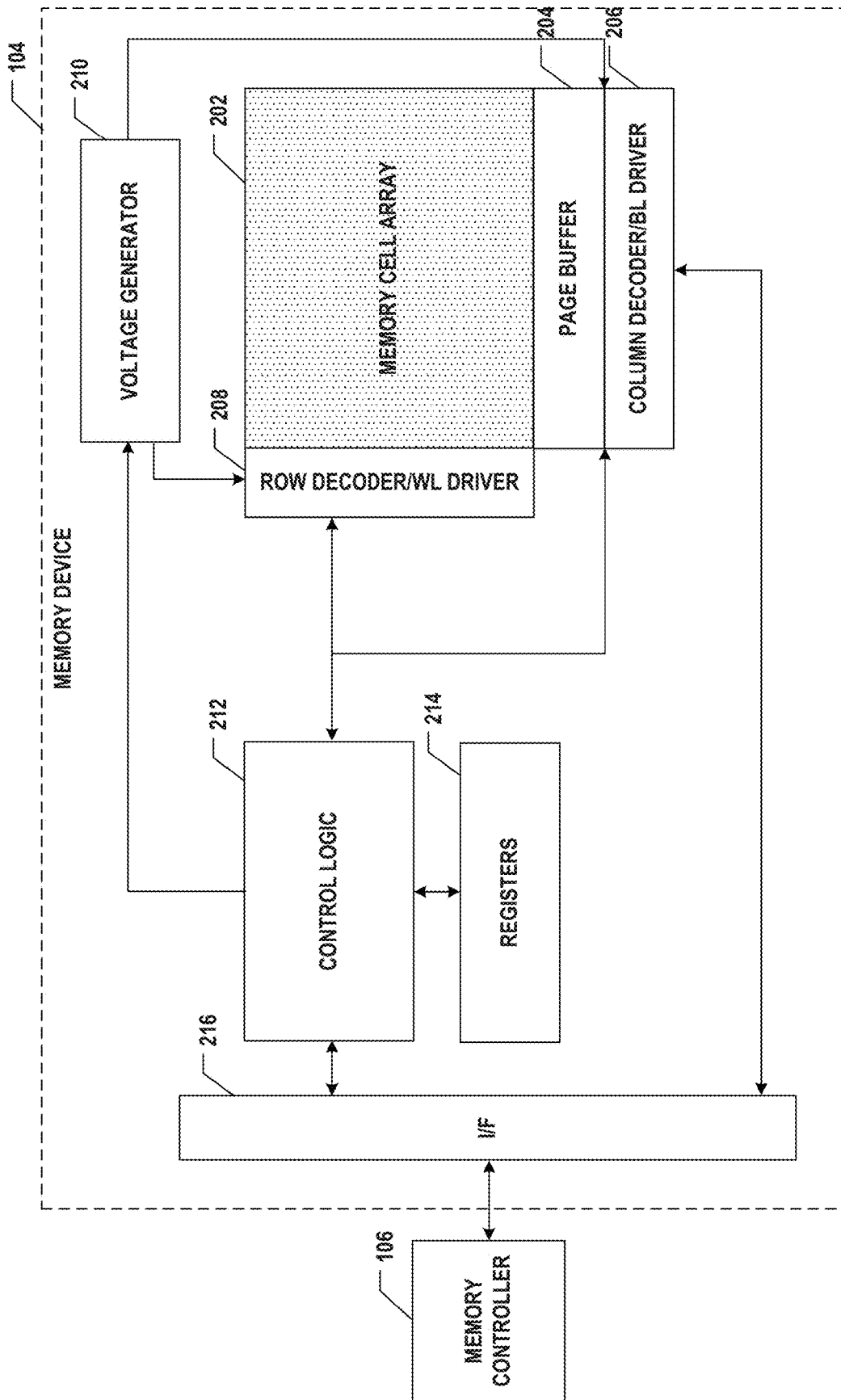


FIG. 2

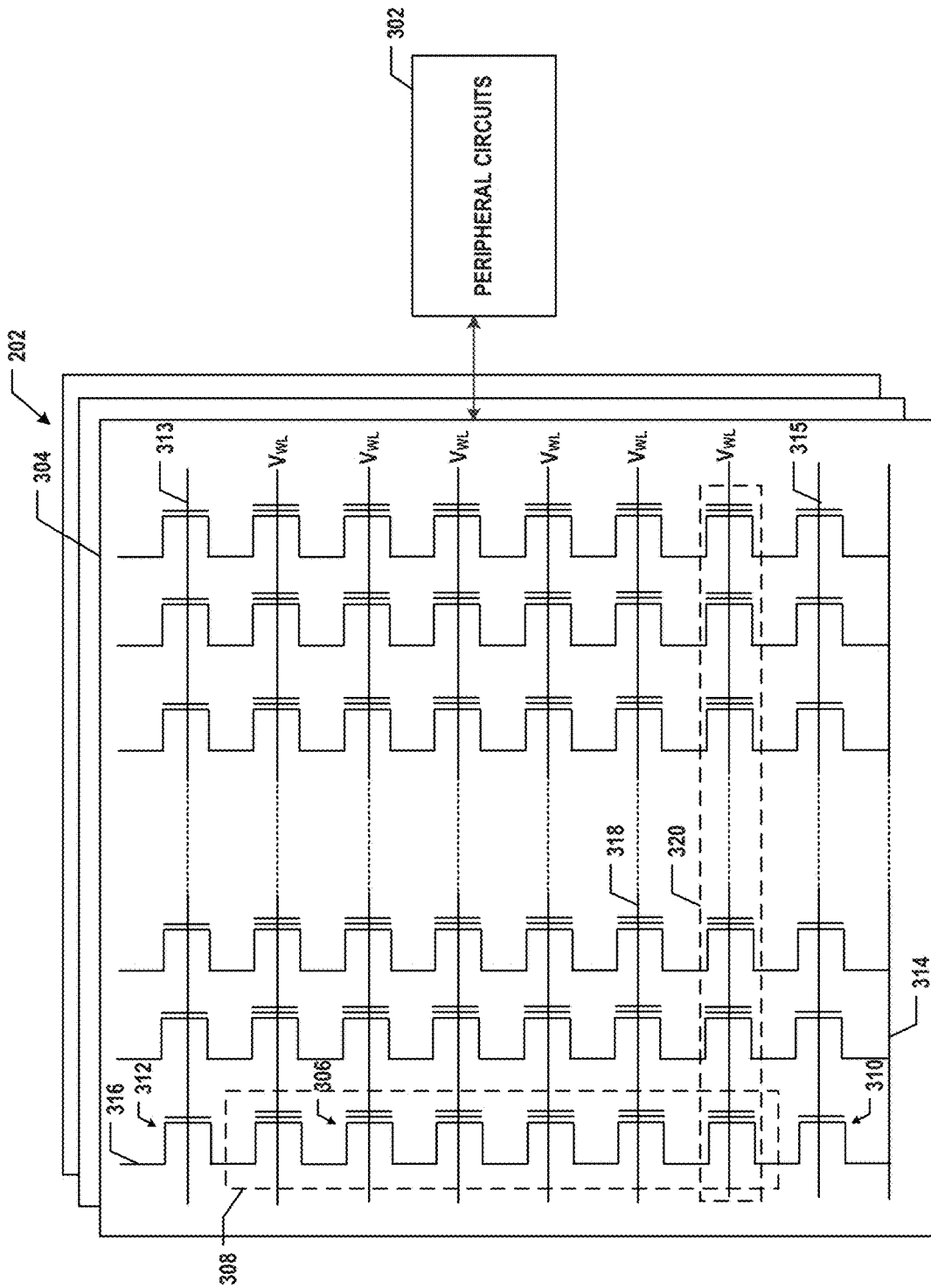


FIG. 3

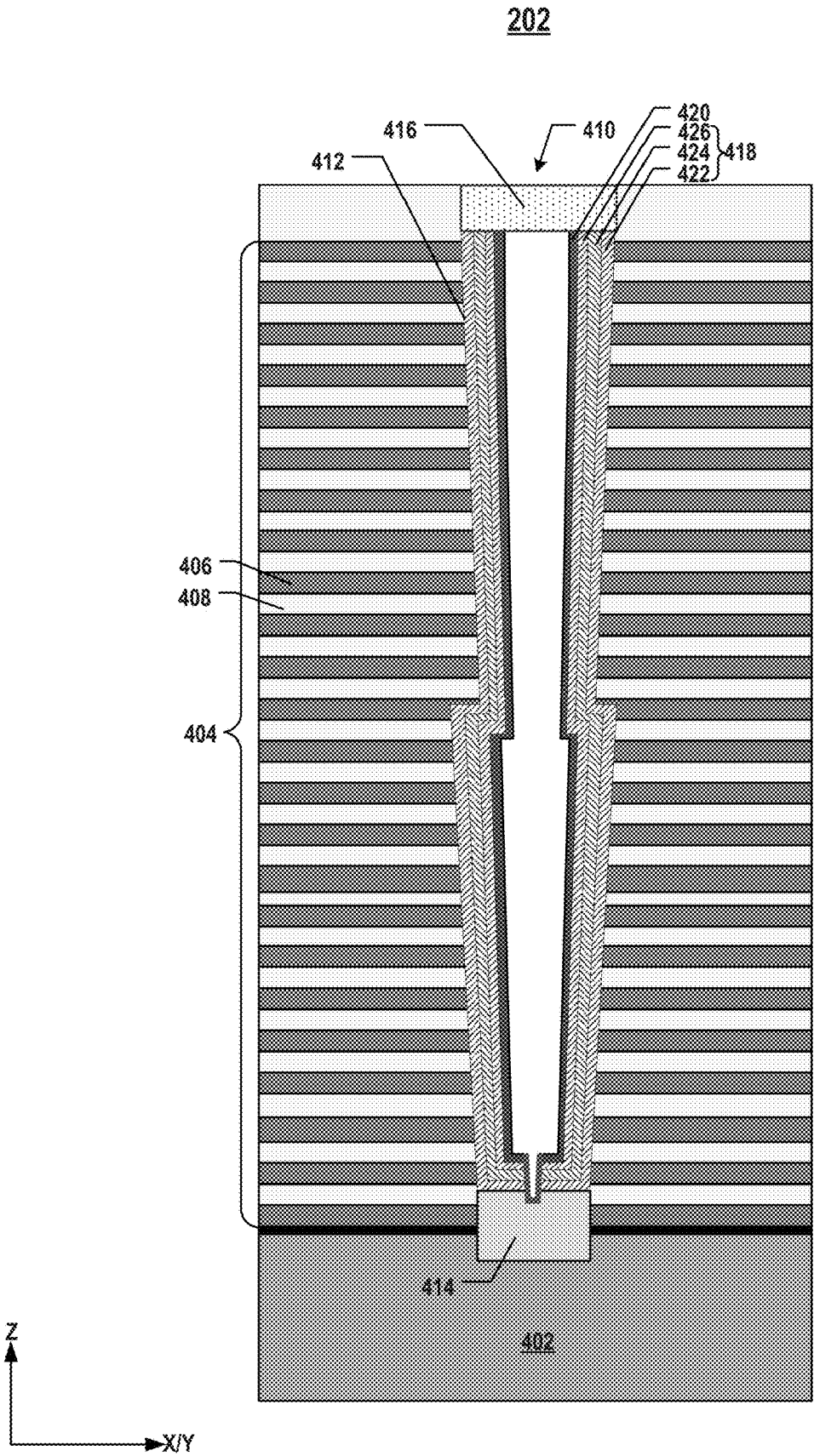


FIG. 4A

202

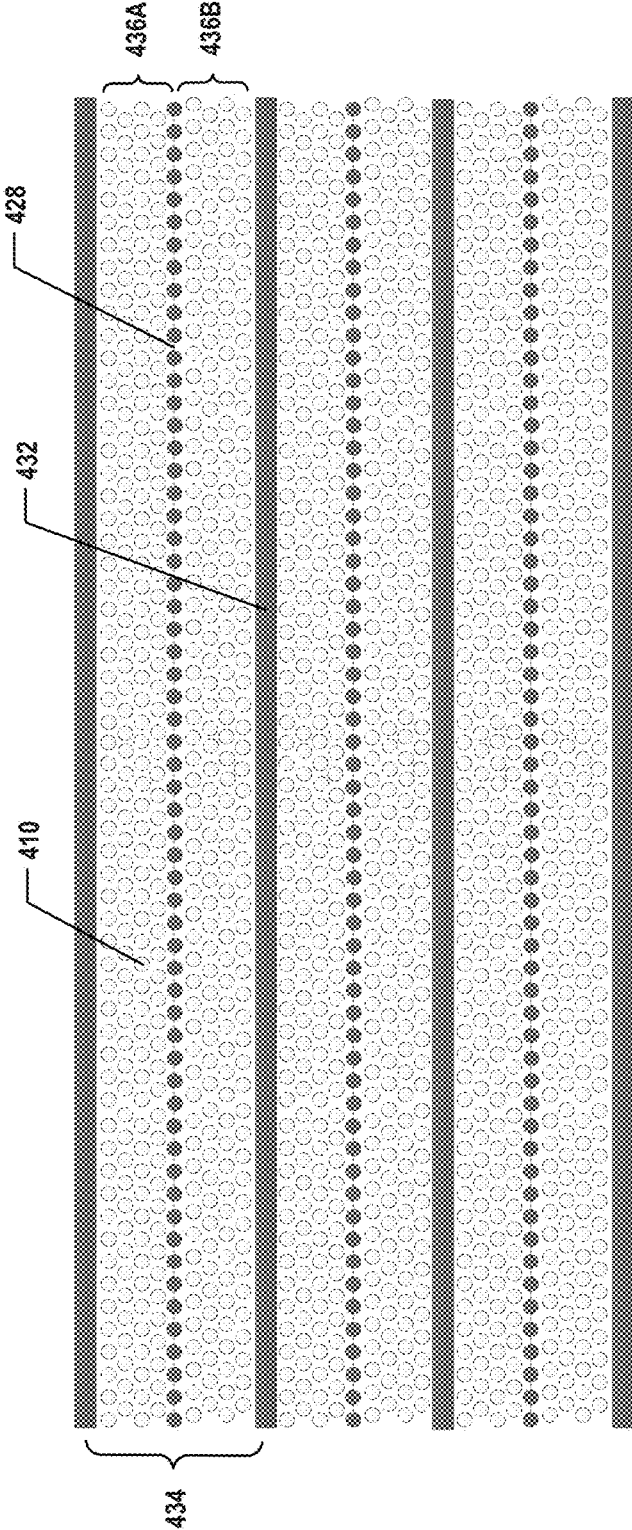


FIG. 4B

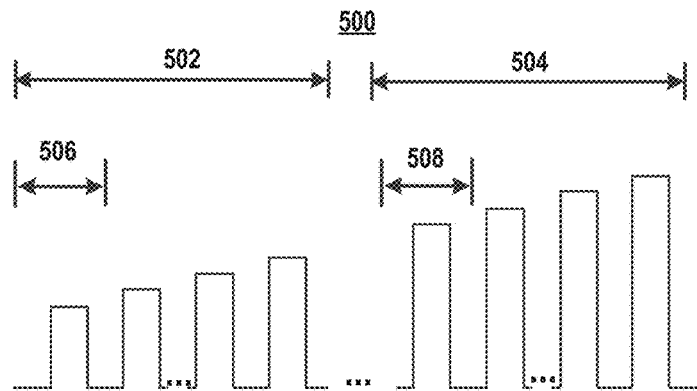


FIG. 5A

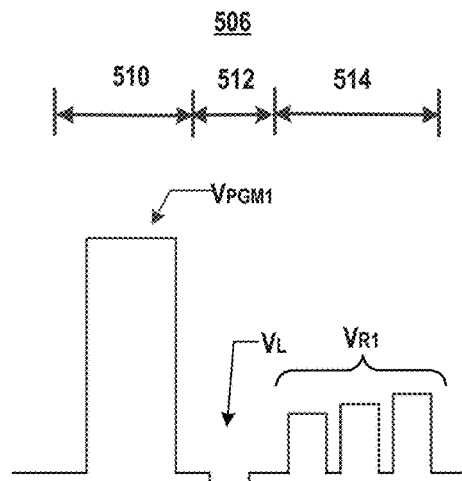


FIG. 5B

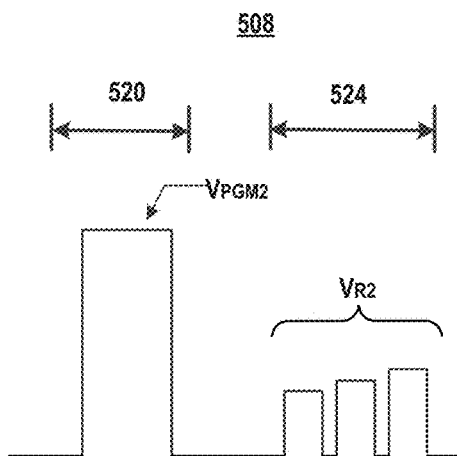


FIG. 5C

600

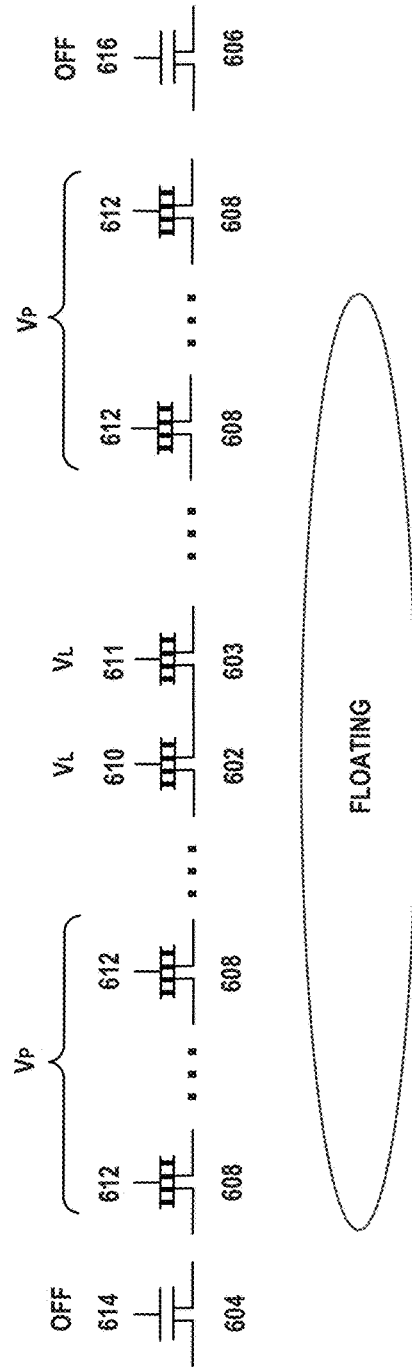


FIG. 6A

506

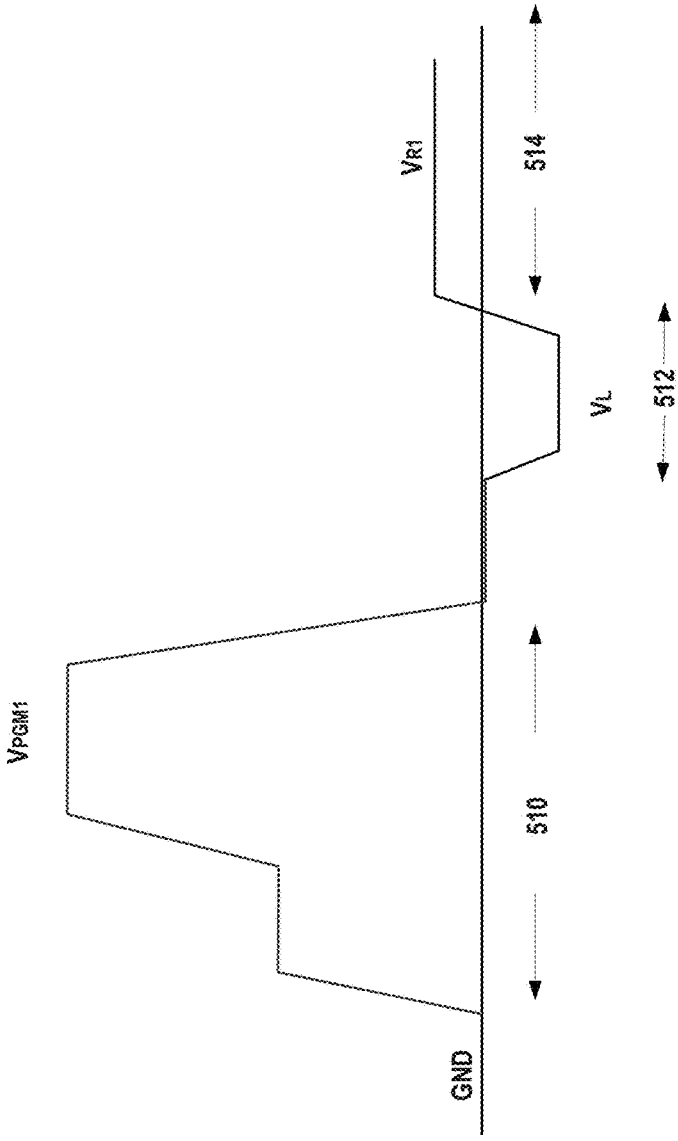


FIG. 6B

WL#	Finger 0		Finger 1		Finger 2		Finger 3		Finger 4		Finger 5	
	1st	2nd	1st	2nd	1st	2nd	1st	2nd	1st	2nd	1st	2nd
0	0	12	1	13	2	14	3	15	4	16	5	17
1	6	24	7	25	8	26	9	27	10	28	11	29
2	18	36	19	37	20	38	21	39	22	40	23	41
3	30	48	31	49	32	50	33	51	34	52	35	53
4	42	60	43	61	44	62	45	63	46	64	47	65
5	54	72	55	73	56	74	57	75	58	76	59	77
...
63	750	762	751	763	752	764	753	765	754	766	755	767

FIG. 7A

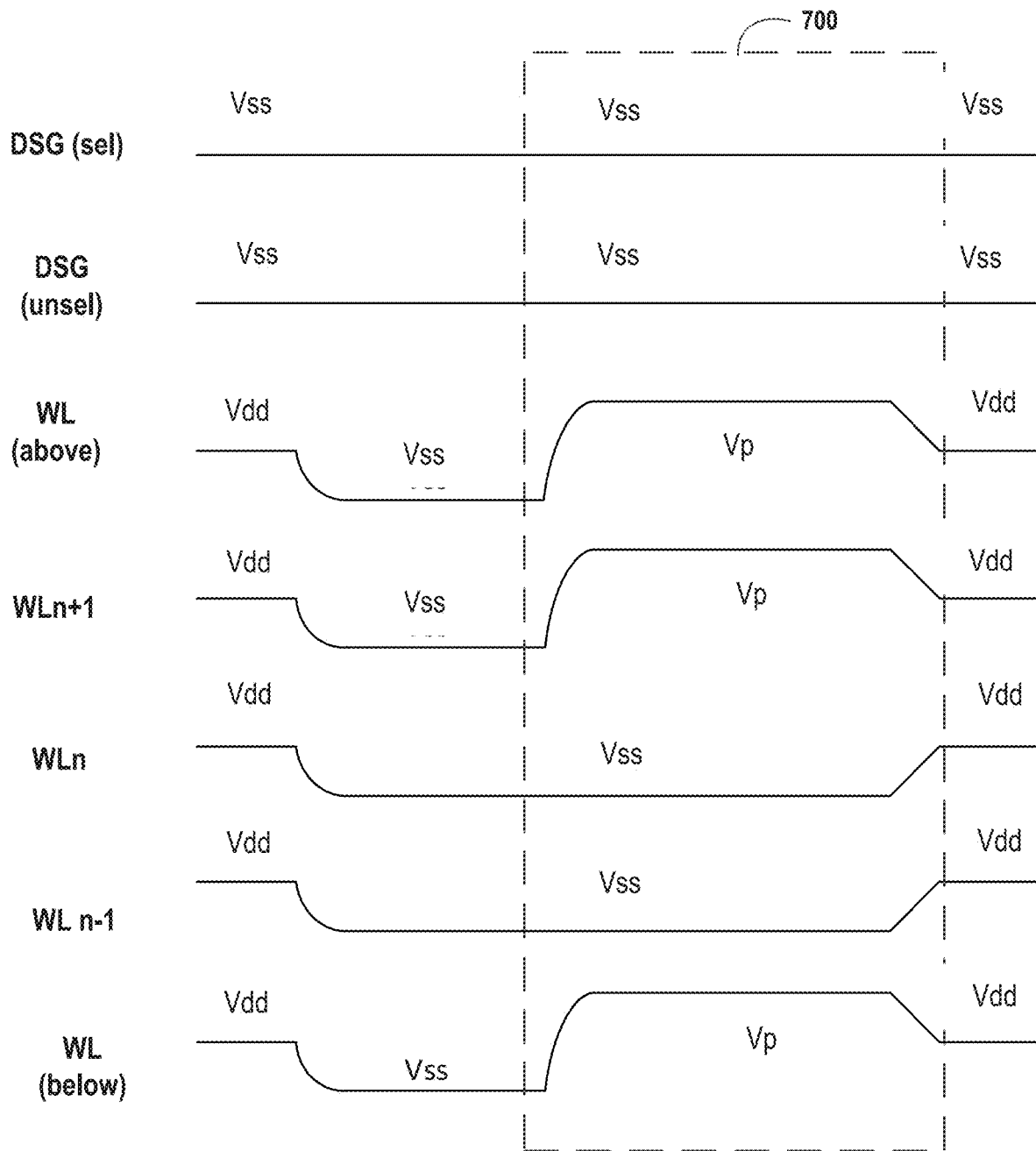


FIG. 7B

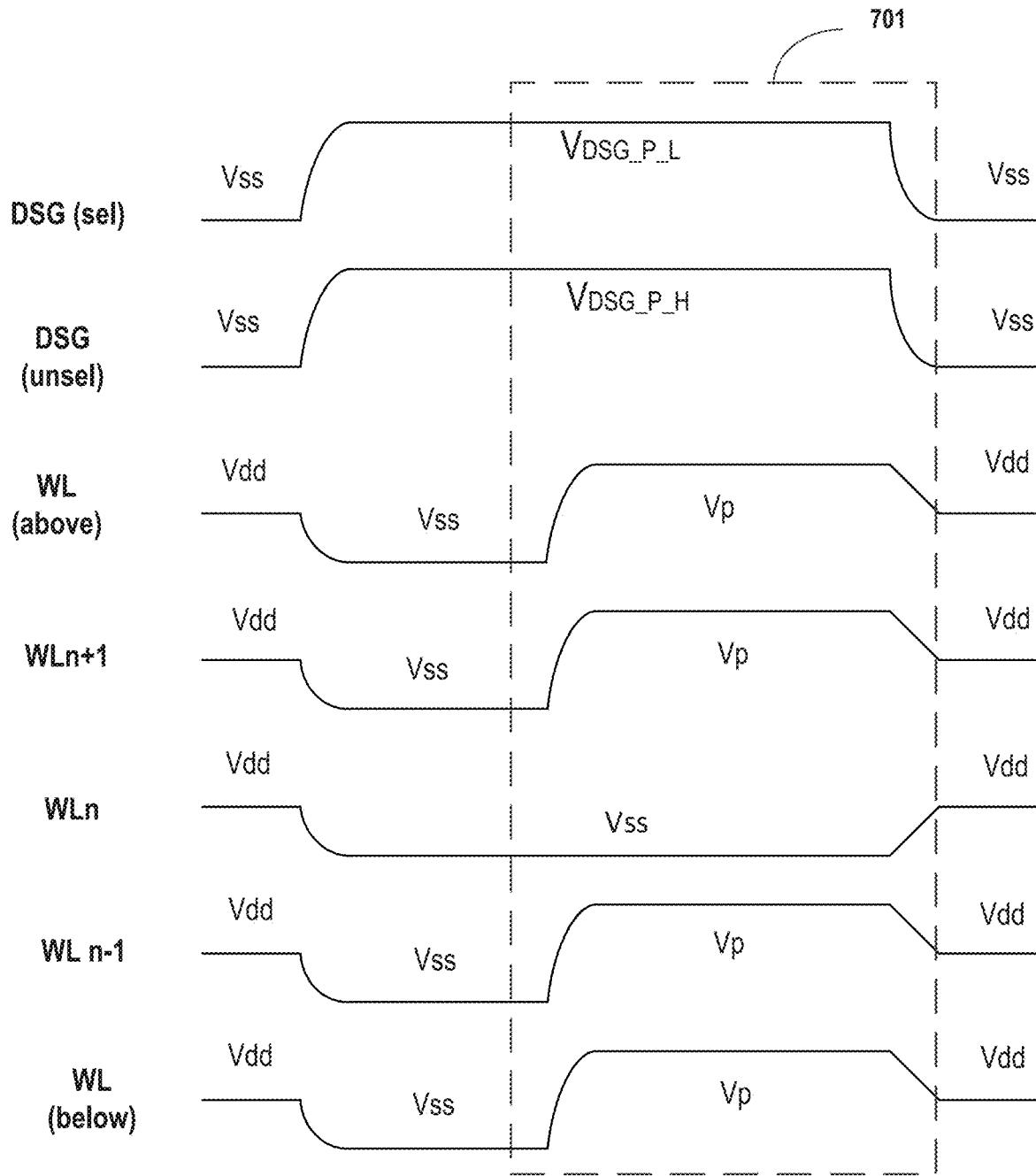


FIG. 7C

WL#	Finger 0		Finger 1		Finger 2		Finger 3		Finger 4		Finger 5	
	1st	2nd	1st	2nd	1st	2nd	1st	2nd	1st	2nd	1st	2nd
0	0	7	1	9	2	11	3	13	4	15	5	17
1	6	19	8	21	10	23	12	25	14	27	16	29
2	18	31	20	33	22	35	24	37	26	39	28	41
3	30	43	32	45	34	47	36	49	38	51	40	53
4	42	55	44	57	46	59	48	61	50	63	52	65
5	54	67	56	69	58	71	60	73	62	75	64	77
...
63	750	762	752	763	754	764	756	765	758	766	760	767

FIG. 8A

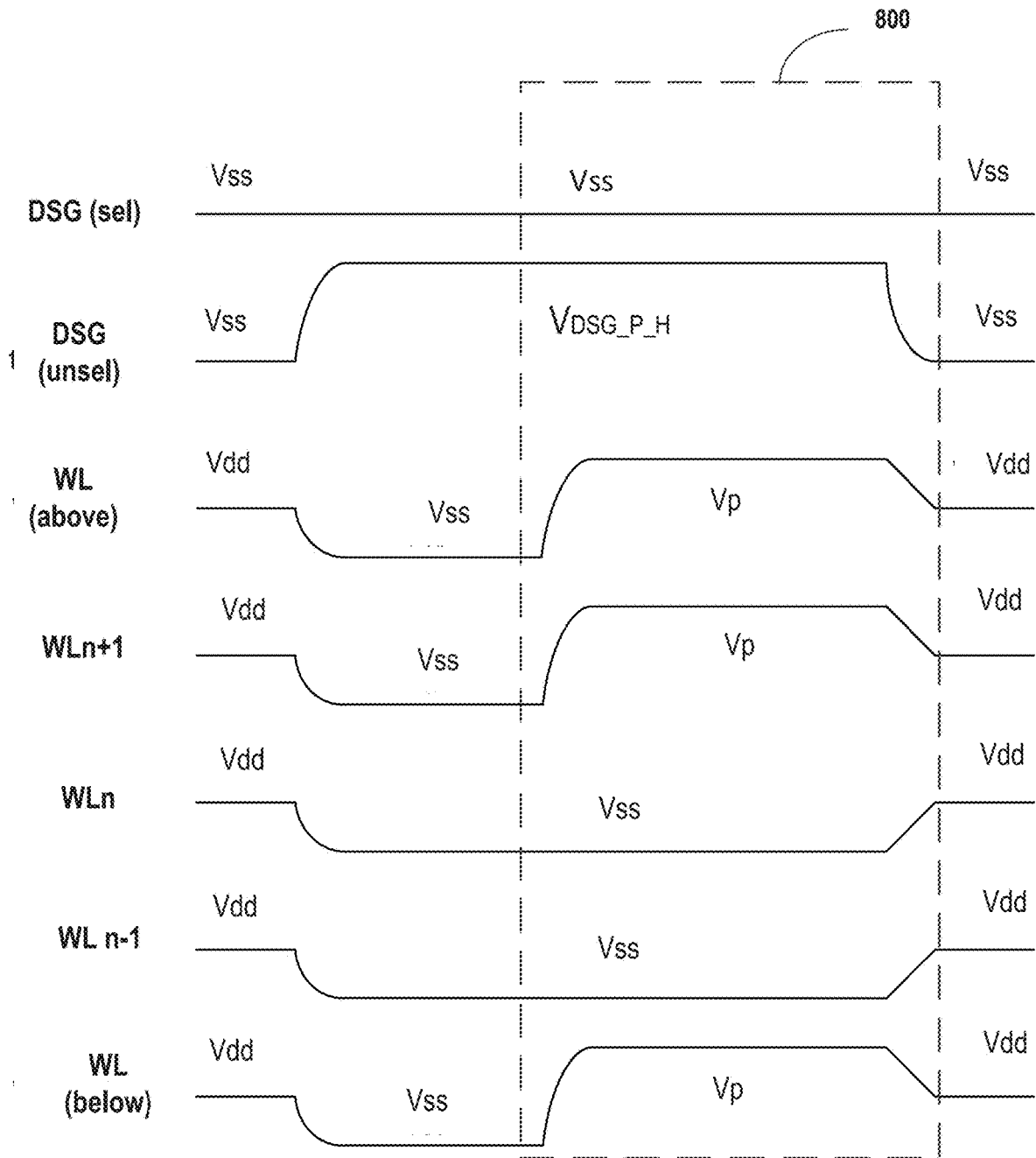


FIG. 8B

900

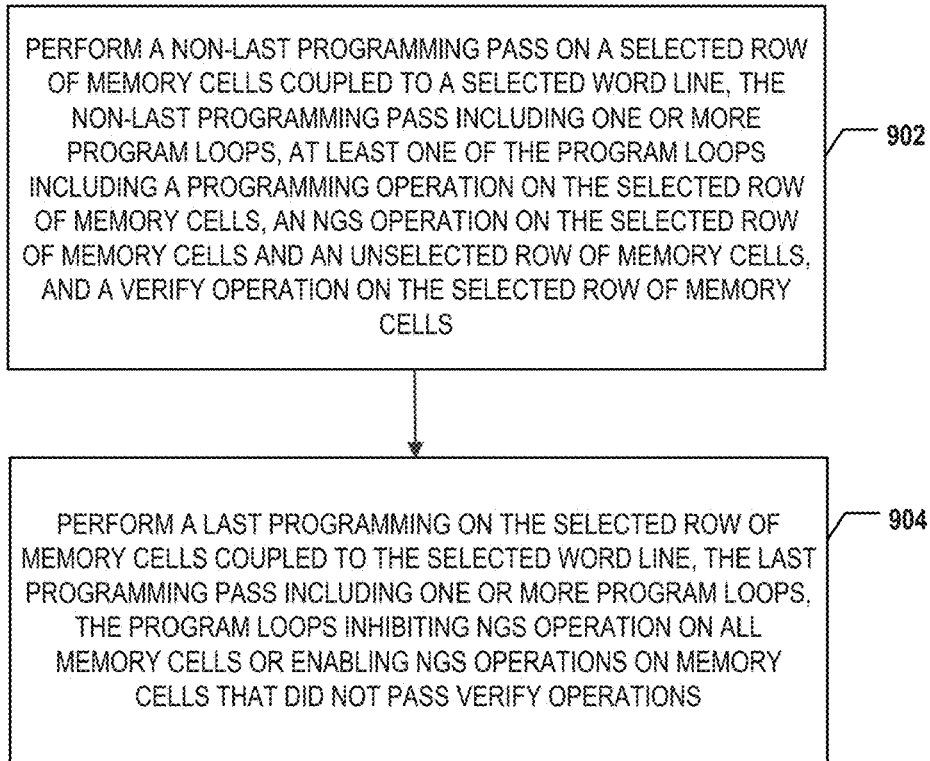


FIG. 9

NEGATIVE GATE STRESS OPERATION IN MULTI-PASS PROGRAMMING AND MEMORY DEVICE THEREOF

CROSS-REFERENCE TO RELATED APPLICATIONS

[0001] This application is continuation of International Application No. PCT/CN2021/083511, filed on Mar. 29, 2021, entitled “NEGATIVE GATE STRESS OPERATION IN MULTI-PASS PROGRAMMING AND MEMORY DEVICE THEREOF,” which is hereby incorporated by reference in its entirety. This application is also related to co-pending U.S. application Ser. No. _____, Attorney Docketing No.: 10018-01-0178-US, filed on even date, entitled “NEGATIVE GATE STRESS OPERATION IN MULTI-PASS PROGRAMMING AND MEMORY DEVICE THEREOF,” which is hereby incorporated by reference in its entirety.

BACKGROUND

[0002] The present disclosure relates to memory devices and operations thereof.

[0003] Flash memory is a low-cost, high-density, non-volatile solid-state storage medium that can be electrically erased and reprogrammed. Flash memory includes NOR Flash memory and NAND Flash memory. Various operations can be performed by Flash memory, such as read, program (write), and erase, to change the threshold voltage of each memory cell to a desired level. For NAND Flash memory, an erase operation can be performed at the block level, a program operation can be performed at the page level, and a read operation can be performed at the cell level.

SUMMARY

[0004] In one aspect, a memory device includes an array of memory cells arranged in a plurality of rows, a plurality of word lines respectively coupled to the plurality of rows of the memory cells, and a peripheral circuit coupled to the word lines and configured to perform multi-pass programming on a selected row of memory cells coupled to a selected word line of the word lines. The multi-pass programming includes a plurality of programming passes. Each of the programming passes includes a programming operation and a verify operation. To perform the multi-pass programming, the peripheral circuit is configured to, in a non-last programming pass of memory cells, perform a negative gate stress (NGS) operation on a memory cell in the selected row of memory cells between the programming operation and the verify operation; and at a same time, perform a NGS operation on a memory cell in an unselected row of memory cells coupled to an unselected word line of the word lines. The unselected word line is adjacent to the selected word line.

[0005] In another aspect, a method for operating a memory device is provided. The memory device includes an array of memory cells arranged in a plurality of rows and a plurality of word lines respectively coupled to the plurality of rows of the memory cells. The method includes performing multi-pass programming on a selected row of memory cells coupled to a selected word line of the word lines. The multi-pass programming includes a plurality of programming passes. Each of the programming passes includes a programming operation and a verify operation. Performing

the multi-pass programming includes, in a non-last programming pass of memory cells, perform a NGS operation on a memory cell in the selected row of memory cells between the programming operation and the verify operation. Performing the multi-pass programming also includes, at a same time, perform a NGS operation on a memory cell in an unselected row of memory cells coupled to an unselected word line of the word lines, the unselected word line being adjacent to the selected word line.

[0006] In still another aspect, a system includes a memory device configured to store data and a memory controller coupled to the memory device and configured to control the memory device. The system includes a memory device configured to store data. The memory device includes an array of memory cells arranged in a plurality of rows, a plurality of word lines respectively coupled to the plurality of rows of the memory cells, and a peripheral circuit coupled to the word lines and configured to perform multi-pass programming on a selected row of memory cells coupled to a selected word line of the word lines. The multi-pass programming includes a plurality of programming passes. Each of the programming passes includes a programming operation and a verify operation. To perform the multi-pass programming, the peripheral circuit is configured to, in a non-last programming pass of memory cells, perform a NGS operation on a memory cell in the selected row of memory cells between the programming operation and the verify operation. To perform the multi-pass programming, the peripheral circuit is configured to, at a same time, perform a NGS operation on a memory cell in an unselected row of memory cells coupled to an unselected word line of the word lines, the unselected word line being adjacent to the selected word line.

BRIEF DESCRIPTION OF THE DRAWINGS

[0007] The accompanying drawings, which are incorporated herein and form a part of the specification, illustrate aspects of the present disclosure and, together with the description, further serve to explain the present disclosure and to enable a person skilled in the pertinent art to make and use the present disclosure.

[0008] FIG. 1A illustrates a block diagram of an exemplary system having a memory device, according to some aspects of the present disclosure.

[0009] FIG. 1B illustrates a diagram of an exemplary memory card having a memory device, according to some aspects of the present disclosure.

[0010] FIG. 1C illustrates a diagram of an exemplary solid-state drive (SSD) having a memory device, according to some aspects of the present disclosure.

[0011] FIG. 2 illustrates a block diagram of an exemplary memory device including a memory cell array and peripheral circuits, according to some aspects of the present disclosure.

[0012] FIG. 3 illustrates a schematic circuit diagram of an exemplary memory device including peripheral circuits, according to some aspects of the present disclosure.

[0013] FIG. 4A illustrates a cross-section of an exemplary memory array device, according to some aspects of the present disclosure.

[0014] FIG. 4B illustrates a top view of a block in an exemplary memory array device, according to some aspects of the present disclosure.

[0015] FIG. 5A illustrates a scheme of multi-pass programming for operating an exemplary memory device, according to some aspects of the present disclosure.

[0016] FIG. 5B illustrates a programming loop with a NGS operation, according to some aspects of the present disclosure.

[0017] FIG. 5C illustrates a programming loop without a NGS operation, according to some aspects of the present disclosure.

[0018] FIG. 6A illustrates a NGS operation on a memory cell in a string in an exemplary memory array device, according to some aspects of the present disclosure.

[0019] FIG. 6B illustrates a voltage waveform applied on a word line coupled to the memory cell in the NGS operation shown in FIG. 6A, according to some aspects of the present disclosure.

[0020] FIG. 7A illustrates an exemplary word-line priority sequence in a memory device, according to some aspects of the present disclosure.

[0021] FIG. 7B illustrates exemplary voltage waveforms applied on word lines coupled to memory cells and select gate transistors in an exemplary NGS operation in a non-last programming pass having a word-line priority sequence, according to some aspects of the present disclosure.

[0022] FIG. 7C illustrates exemplary voltage waveforms applied on word lines coupled to memory cells and select gate transistors in a known NGS operation, according to some aspects of the present disclosure.

[0023] FIG. 8A illustrates an exemplary sawtooth sequence in a memory device, according to some aspects of the present disclosure.

[0024] FIG. 8B illustrates exemplary voltage waveforms applied on word lines coupled to memory cells and select gate transistors in an exemplary NGS operation in a non-last programming pass having a sawtooth sequence, according to some aspects of the present disclosure.

[0025] FIG. 9 illustrates a flowchart of an exemplary method for performing multi-pass programming on a selected row of memory cells, according to some aspects of the present disclosure.

[0026] Aspects of the present disclosure will be described with reference to the accompanying drawings.

DETAILED DESCRIPTION

[0027] Although specific configurations and arrangements are discussed, it should be understood that this is done for illustrative purposes only. As such, other configurations and arrangements can be used without departing from the scope of the present disclosure. Also, the present disclosure can also be employed in a variety of other applications. Functional and structural features as described in the present disclosures can be combined, adjusted, and modified with one another and in ways not specifically depicted in the drawings, such that these combinations, adjustments, and modifications are within the scope of the present disclosures.

[0028] In general, terminology may be understood at least in part from usage in context. For example, the term “one or more” as used herein, depending at least in part upon context, may be used to describe any feature, structure, or characteristic in a singular sense or may be used to describe combinations of features, structures, or characteristics in a plural sense. Similarly, terms, such as “a,” “an,” or “the,” again, may be understood to convey a singular usage or to convey a plural usage, depending at least in part upon

context. In addition, the term “based on” may be understood as not necessarily intended to convey an exclusive set of factors and may, instead, allow for existence of additional factors not necessarily expressly described, again, depending at least in part on context.

[0029] It should be readily understood that the meaning of “on,” “above,” and “over” in the present disclosure should be interpreted in the broadest manner such that “on” not only means “directly on” something but also includes the meaning of “on” something with an intermediate feature or a layer therebetween, and that “above” or “over” not only means the meaning of “above” or “over” something but can also include the meaning it is “above” or “over” something with no intermediate feature or layer therebetween (i.e., directly on something).

[0030] Further, spatially relative terms, such as “beneath,” “below,” “lower,” “above,” “upper,” and the like, may be used herein for ease of description to describe one element or feature’s relationship to another element(s) or feature(s) as illustrated in the figures. The spatially relative terms are intended to encompass different orientations of the device in use or operation in addition to the orientation depicted in the figures. The apparatus may be otherwise oriented (rotated 90 degrees or at other orientations) and the spatially relative descriptors used herein may likewise be interpreted accordingly.

[0031] As used herein, the term “layer” refers to a material portion including a region with a thickness. A layer can extend over the entirety of an underlying or overlying structure or may have an extent less than the extent of an underlying or overlying structure. Further, a layer can be a region of a homogeneous or inhomogeneous continuous structure that has a thickness less than the thickness of the continuous structure. For example, a layer can be located between any pair of horizontal planes between, or at, a top surface and a bottom surface of the continuous structure. A layer can extend horizontally, vertically, and/or along a tapered surface. A substrate can be a layer, can include one or more layers therein, and/or can have one or more layer thereupon, thereabove, and/or therebelow. A layer can include multiple layers. For example, an interconnect layer can include one or more conductor and contact layers (in which interconnect lines and/or via contacts are formed) and one or more dielectric layers.

[0032] Charge-trapping material has been used for retention of data in a NAND Flash memory. For example, a charge-trapping material can be used in a charge-trapping layer in a NAND memory string (e.g., memory channel). However, a charge-trapping device, e.g., a memory device having a charge-trapping layer for data retention, can have reliability issues due to the nature of the charge-trapping material.

[0033] A common issue of a charge-trapping device is known as a fast initial charge loss (or early retention) issue, which is a fast relaxation behavior in which charges escape from the charge-trapping layer shortly after a programming operation. This behavior is believed to cause by the shallowly-trapped charges and can result in a threshold voltage of a memory cell to drift. The drifting of the threshold voltage can lead to degraded programming distributions.

[0034] In a NAND Flash memory, the intersections of word lines and strings form a plurality of memory cells. The block includes a plurality of fingers, and each finger includes a pair of fingers. Each string is coupled to a bit line. Strings

in a finger are coupled to a drain select gate (DSG). A memory cell stores data in the form of a threshold voltage, which represents the lowest voltage at which the memory cell can be switched on. For example, the threshold voltage range of a 2-bit multi-level cell (MLC) NAND Flash memory cell is divided into four regions. The region in which the threshold voltage of a memory cell falls represents the memory cell's current state, which can be an erased (or ER) state and three higher data states. A programming pass may use a set of increasing program voltages/pulses which are applied on the word line coupled to a memory cell to program the memory cell by setting the threshold voltage of the memory cell to the desired states. Each program voltage/pulse is applied in a programming operation and is followed by a verify operation, which employs one or more verify voltages to determine whether the memory cell has completed programming. After all the memory cells are programmed, the data in the memory cells can be read back in a read operation.

[0035] Multi-pass programming can be used in programming memory cells. In multi-pass programming, multiple programming passes are employed consecutively. Multi-pass programming can reduce neighboring word line interference (NWI), which refers to an increase in the threshold voltage of a memory cell connected to one word line when the neighboring (adjacent) memory cells (e.g., in the same string and coupled to other word lines) are programmed. Multi-pass programming can reduce the NWI by programming the memory cells to intermediate threshold voltage distributions in non-last programming pass(es), and programming the memory cells to the final threshold voltage distribution in the last programming pass.

[0036] As mentioned above, shallowly-trapped charges may cause programming distribution to degrade. To solve the issue of degraded programming distribution, a negative gate stress (NGS) operation has been used in the multi-pass programming to remove at least some shallowly-trapped charges and tighten the threshold voltage distribution. However, a NGS operation may decrease a read window budget (RWB), i.e., a threshold voltage window between erased and higher data states needed for reading operation of a memory cell, and is thus not suitable to be enabled on a memory cell after the memory cell already passes a verify operation. In a NGS operation, memory cells passed the verify operation immediately prior to the NGS operation, and memory cells not passed the verify operation immediately prior to the NGS operation are applied with different combinations of voltages such that the memory cells passed the verify operation would not undergo the NGS operation and only the memory cells not passed the verify operation would undergo the NGS operation. For example, when programming memory cells row by row, different voltages are applied on the DSGs and bit lines coupled to memory cells (e.g., in the same row) passed and not passed the verify operation, respectively, such that only the memory cells not passed the verify operation undergo NGS operations. The operation of the NAND memory can be complex, and the power consumption of the operation can be undesirably high. Sometimes, the distributions of the threshold voltage of memory cells that have already undergone a NGS operation are not desirably narrow, impacting the reading operation.

[0037] The present disclosure provides a novel NGS scheme for multi-pass programming in a memory device,

the memory device, and a system thereof. The NGS scheme is enabled in at least one non-last programming pass of the multi-pass programming to remove shallowly-trapped charges in memory cells passed and not passed a respective verify operation immediately-prior to the NGS operation. Different from a known NGS scheme, which is enabled only on one selected row of memory cells, the novel NGS scheme is enabled on two rows of memory cells at the same time. In an example, the novel NGS scheme is enabled in a selected row that is being programmed and an unselected row that is programmed immediately prior to the selected row of memory cells. The unselected row can be immediately above or immediately below the selected row, depending on the direction in which the word lines are programmed. In a word-line priority sequence, memory cells in the selected and unselected rows, passed and not passed the respective verify operation prior to the NGS operation, may each undergo a respective NGS operation. In a sawtooth sequence, only memory cells not undergoing the last programming pass may undergo a respective NGS operation. The NGS operations can further remove the shallowly-trapped charges in the memory cells that have already passed the respective verify operation, and further narrow the distributions of threshold voltage, increasing the RWB. In the last programming pass of the multi-pass programming, when a selected row of memory cells are being programmed, NGS operations are only enabled on memory cells not passed a respective verify operation immediately prior to the NGS operation or not enabled on any memory cells. The RWB of a memory cell thus would not be decreased by NGS operations.

[0038] To enable NGS operations on memory cells in a selected row that is being programmed and an unselected row that has been already programmed, source-select gates (SSGs) of all the strings in which all the memory cells are in are turned off. If the voltages are applied on the word lines in a word-line priority sequence, a same low voltage may be applied on the DSGs of all the strings in which all the memory cells in the selected row and the unselected row are located. The DSGs of all the strings are thus turned off. If the voltages are applied on the word lines in a sawtooth sequence, a low voltage may be applied on the DSGs of a selected finger in which (i) the last programming pass has been performed on the selected finger and at least one memory cell in the selected and unselected rows did not pass the respective verify operation or (ii) the last programming pass has not been performed on these memory cells. Meanwhile, a high positive voltage may be applied on the DSGs of an unselected finger in which (i) all the memory cells in the selected and unselected rows passed the respective verify operation and (ii) these memory cells have undergone the last programming pass. Along with bit line voltages applied on respective strings in each finger, selected strings and unselected strings can be respectively chosen such that a selected string (i.e., having a memory cell in the selected and unselected row to undergo a NGS) is to undergo a potential boost and an unselected string (i.e., having no memory cell in the selected and unselected row to undergo a NGS) is grounded. A relatively high positive voltage, e.g., higher than V_{DD} , is applied on word lines above and below the word lines coupled to the memory cells in the selected and unselected rows. The potential of the strings, i.e., all strings for the word-line priority sequence and the selected strings for the sawtooth sequence, can be boosted. These strings are

thus each in a floating state, and the potential in the strings increases. A low voltage is applied on the word line coupled to the selected row and unselected row of memory cells such that a NGS operation can be enabled in the memory cells in the two rows and the strings having the potential boost. This can enable “an erase” of the shallowly-trapped charges such that these memory cells can have the shallowly-trapped charges further removed. To avoid the decrease of RWB of the memory cells, the novel NGS scheme is enabled in a non-last programming pass. In some implementations, because a low voltage, e.g., ground or a negative voltage, is applied on the DSGs of the strings having the potential boost, the power consumption can be reduced.

[0039] FIG. 1A illustrates a block diagram of an exemplary system **100** having a memory device, according to some aspects of the present disclosure. System **100** can be a mobile phone, a desktop computer, a laptop computer, a tablet, a vehicle computer, a gaming console, a printer, a positioning device, a wearable electronic device, a smart sensor, a virtual reality (VR) device, an augmented reality (AR) device, or any other suitable electronic devices having storage therein. As shown in FIG. 1A, system **100** can include a host **108** and a memory system **102** having one or more memory devices **104** and a memory controller **106**. Host **108** can be a processor of an electronic device, such as a central processing unit (CPU), or a system-on-chip (SoC), such as an application processor (AP). Host **108** can be configured to send or receive the data to or from memory devices **104**.

[0040] Memory device **104** can be any memory devices disclosed herein, such as a NAND Flash memory device. Consistent with the scope of the present disclosure, memory controller **106** may control the multi-pass programming on memory device **104** such that a NGS operation is enabled on memory cells in two rows at the same time, in a non-last programming pass of the multi-pass programming. The peripheral circuits, such as the word line drivers, may apply respective voltages, on the DSGs of each memory string coupled to the selected word line, and may apply a low or negative voltage on the selected word line and unselected word line to enable a NGS operation on all memory cells coupled to the two word lines or a portion of the memory cells coupled to the two word lines during a non-last programming pass.

[0041] Memory controller **106** is coupled to memory device **104** and host **108** and is configured to control memory device **104**, according to some implementations. Memory controller **106** can manage the data stored in memory device **104** and communicate with host **108**. In some implementations, memory controller **106** is designed for operating in a low duty-cycle environment like secure digital (SD) cards, compact Flash (CF) cards, universal serial bus (USB) Flash drives, or other media for use in electronic devices, such as personal computers, digital cameras, mobile phones, etc. In some implementations, memory controller **106** is designed for operating in a high duty-cycle environment SSDs or embedded multi-media-cards (eMMCs) used as data storage for mobile devices, such as smartphones, tablets, laptop computers, etc., and enterprise storage arrays. Memory controller **106** can be configured to control operations of memory device **104**, such as read, erase, and program operations. Memory controller **106** can also be configured to manage various functions with respect to the data stored or to be stored in memory device **104**

including, but not limited to bad-block management, garbage collection, logical-to-physical address conversion, wear leveling, etc. In some implementations, memory controller **106** is further configured to process error correction codes (ECCs) with respect to the data read from or written to memory device **104**. Any other suitable functions may be performed by memory controller **106** as well, for example, programming memory device **104**. Memory controller **106** can communicate with an external device (e.g., host **108**) according to a particular communication protocol. For example, memory controller **106** may communicate with the external device through at least one of various interface protocols, such as a USB protocol, an MMC protocol, a peripheral component interconnection (PCI) protocol, a PCI-express (PCI-E) protocol, an advanced technology attachment (ATA) protocol, a serial-ATA protocol, a parallel-ATA protocol, a small computer small interface (SCSI) protocol, an enhanced small disk interface (ESDI) protocol, an integrated drive electronics (IDE) protocol, a Firewire protocol, etc.

[0042] Memory controller **106** and one or more memory devices **104** can be integrated into various types of storage devices, for example, be included in the same package, such as a universal Flash storage (UFS) package or an eMMC package. That is, memory system **102** can be implemented and packaged into different types of end electronic products. In one example as shown in FIG. 1B, memory controller **106** and a single memory device **104** may be integrated into a memory card **112**. Memory card **112** can include a PC card (PCMCIA, personal computer memory card international association), a CF card, a smart media (SM) card, a memory stick, a multimedia card (MMC, MMCmicro), an SD card (SD, miniSD, microSD, SDHC), a UFS, etc. Memory card **112** can further include a memory card connector **114** coupling memory card **112** with a host (e.g., host **108** in FIG. 1A). In another example as shown in FIG. 1C, memory controller **106** and multiple memory devices **104** may be integrated into an SSD **116**. SSD **116** can further include an SSD connector **118** coupling SSD **116** with a host (e.g., host **108** in FIG. 1A). In some implementations, the storage capacity and/or the operation speed of SSD **116** is greater than those of memory card **112**.

[0043] FIG. 2 illustrates a diagram of an exemplary memory device **104**, e.g., a NAND Flash memory, having a memory cell array **202** and peripheral circuits including a page buffer **204**, a column decoder/bit line driver **206**, a row decoder/word line driver **208**, a voltage generator **210**, control logic **212**, registers **214**, and an interface **216**. FIG. 3 illustrates a schematic circuit diagram of an exemplary memory device **104** including a memory cell array **202** and peripheral circuits **302** coupled to memory cell array **202**. For ease of illustration, some components in FIGS. 2 and 3 are described together. Peripheral circuits **302** can include page buffer **204**, column decoder/bit line driver **206**, row decoder/word line driver **208**, voltage generator **210**, control logic **212**, registers **214**, and interface **216** in FIG. 2. It is understood that in some examples, additional peripheral circuits may be included as well.

[0044] As shown in FIG. 3, memory cell array **202** can be a NAND Flash memory cell array in which memory cells **306** are provided in the form of an array of NAND memory strings **308** each extending vertically above a substrate (not shown). In some implementations, each NAND memory string **308** includes a plurality of memory cells **306** coupled

in series and stacked vertically. Each memory cell **306** can hold a continuous, analog value, such as an electrical voltage or charge, that depends on the number of electrons trapped within a region of memory cell **306**. Each memory cell **306** can be either a floating gate type of memory cell including a floating-gate transistor or a charge trap type of memory cell including a charge-trap transistor.

[0045] In some implementations, each memory cell **306** is a single-level cell (SLC) that has two possible memory states and thus, can store one bit of data. For example, the first memory state “0” can correspond to a first range of voltages, and the second memory state “1” can correspond to a second range of voltages. In some implementations, each memory cell **306** is a multi-level cell (MLC) that is capable of storing more than a single bit of data in more than four memory states. For example, the MLC can store two bits per cell, three bits per cell (also known as triple-level cell (TLC)), or four bits per cell (also known as a quad-level cell (QLC)). Each MLC can be programmed to assume a range of possible nominal storage values. In one example, if each MLC stores two bits of data, then the MLC can be programmed to assume one of three possible programming levels from an erased state by writing one of three possible nominal storage values to the cell. A fourth nominal storage value can be used for the erased state.

[0046] As shown in FIG. 3, each NAND memory string **308** can include an SSG **310** at its source end and a DSG **312** at its drain end. SSG **310** and DSG **312** are respective gate electrodes of an SSG transistor and a DSG transistor and can be configured to activate selected NAND memory strings **308** (columns of the array) during read and program operations. In some implementations, SSGs **310** of NAND memory strings **308** in the same block **304** are coupled through a same source line (SL) **314**, e.g., a common SL, for example, to the ground. DSG **312** of each NAND memory string **308** is coupled to a respective bit line **316** from which data can be read via an output bus (not shown), according to some implementations. In some implementations, each NAND memory string **308** is configured to be selected or deselected by applying a select voltage (e.g., above the threshold voltage of the transistor having DSG **312**) or a deselect voltage (e.g., 0 V) to respective DSG **312** through one or more DSG lines **313** and/or by applying a select voltage (e.g., above the threshold voltage of the transistor having SSG **310**) or a deselect voltage (e.g., 0 V) to respective SSG **310** through one or more SSG lines **315**.

[0047] As shown in FIG. 3, NAND memory strings **308** can be organized into multiple blocks **304**, each of which can have a common source line **314**. In some implementations, each block **304** is the basic data unit for erase operations, i.e., all memory cells **306** on the same block **304** are erased at the same time. Memory cells **306** of adjacent NAND memory strings **308** can be coupled through word lines **318** that select which row of memory cells **306** is affected by read and program operations. In some implementations, each word line **318** is coupled to a page **320** of memory cells **306**, which is the basic data unit for program operations. The size of one page **320** in bits can correspond to the number of NAND memory strings **308** coupled by word line **318** in one block **304**. Each word line **318** can include a plurality of control gates (gate electrodes) at each memory cell **306** in respective page **320** and a gate line coupling the control gates.

[0048] Peripheral circuits **302** can be coupled to memory cell array **202** through bit lines **316**, word lines **318**, source lines **314**, SSG lines **315**, and DSG lines **313**. Peripheral circuits **302** may apply voltages on bit lines **316**, word lines **318**, source lines **314**, SSG lines **315**, and DSG lines **313** to perform multi-pass programming including the proposed NGS scheme in a non-last programming pass. As described above, peripheral circuits **302** can include any suitable circuits for facilitating the operations of memory cell array **202** by applying and sensing voltage signals and/or current signals through bit lines **316** to and from each target memory cell **306** through word lines **318**, source lines **314**, SSG lines **315**, and DSG lines **313**. Peripheral circuits **302** can include various types of peripheral circuits formed using MOS technologies.

[0049] FIG. 4A illustrates a cross-section of an exemplary memory cell array **202**, according to some aspects of the present disclosure. As shown in FIG. 4A, memory cell array **202** includes a NAND memory string **410**, which can be an example of a NAND memory string **308** in FIG. 3, extending vertically above a substrate **402**. Substrate **402** can include silicon (e.g., single crystalline silicon), silicon germanium (SiGe), gallium arsenide (GaAs), germanium (Ge), silicon on insulator (SOI), germanium on insulator (GOI), or any other suitable materials. It is noted that x, y, and z axes are included in FIG. 4A to further illustrate the spatial relationship of the components in memory cell array **202**. Substrate **402** includes two lateral surfaces (e.g., a top surface and a bottom surface) extending laterally in the x-direction (i.e., the lateral direction). As used herein, whether one component is “on,” “above,” or “below” another component of a semiconductor structure (e.g., memory cell array **202**) is determined relative to the substrate of the semiconductor structure (e.g., substrate **402**) in the z-direction (i.e., the vertical direction or depth direction) when the substrate is positioned in the lowest plane of the semiconductor structure in the z-direction. The same notion for describing the spatial relationship is applied throughout the present disclosure.

[0050] As shown in FIG. 4A, NAND memory string **410** extends vertically through a memory stack **404** having interleaved gate conductive layers **406** and gate-to-gate dielectric layers **408** above substrate **402**. Gate conductive layers **406** and gate-to-gate dielectric layers **408** in memory stack **404** can alternate in the vertical direction. Each gate conductive layer **406** can include conductive materials including, but not limited to, tungsten (W), cobalt (Co), copper (Cu), aluminum (Al), polysilicon, doped silicon, silicides, or any combination thereof. In some implementations, each gate conductive layer **406** includes a metal layer, such as a tungsten layer. In some implementations, each gate conductive layer **406** includes a doped polysilicon layer. Each gate conductive layer **406** can include control gates surrounding the memory cells (e.g., memory cells **306** in FIG. 3), a DSG (e.g., DSG **312** in FIG. 3), or an SSG (e.g., SSG **310** in FIG. 3), and can extend laterally as a DSG line (e.g., DSG line **313** in FIG. 3) at the top of memory stack **404**, an SSG line (e.g., SSG line **315** in FIG. 3) at the bottom of memory stack **404**, or a word line between the DSG line and the SSG line (e.g., word lines **318** in FIG. 3).

[0051] As shown in FIG. 4A, NAND memory string **410** includes a channel structure **412** extending vertically through memory stack **404**. In some implementations, channel structure **412** includes a channel hole filled with semiconductor material(s) (e.g., as a semiconductor channel **420**)

and dielectric material(s) (e.g., as a memory film **418**). In some implementations, semiconductor channel **420** includes silicon, such as amorphous silicon, polysilicon, or single crystalline silicon. In some implementations, memory film **418** is a composite dielectric layer including a tunneling layer **426**, a storage layer **424** (also known as a “charge trap/storage layer”), and a blocking layer **422**. Channel structure **412** can have a cylinder shape (e.g., a pillar shape). Semiconductor channel **420**, tunneling layer **426**, storage layer **424**, blocking layer **422** are arranged radially from the center toward the outer surface of the pillar in this order, according to some implementations. Tunneling layer **426** can include silicon oxide, silicon oxynitride, or any combination thereof. Storage layer **424** can include silicon nitride, silicon oxynitride, silicon, or any combination thereof. Blocking layer **422** can include silicon oxide, silicon oxynitride, high dielectric constant (high-k) dielectrics, or any combination thereof. In one example, memory film **418** can include a composite layer of silicon oxide/silicon oxynitride/silicon oxide (ONO).

[0052] In some implementations, NAND memory string **410** further includes a semiconductor plug **414** in the lower portion (e.g., at the lower end) of NAND memory string **410**. Semiconductor plug **414** can include a semiconductor material, such as single-crystal silicon, which is epitaxially grown from substrate **402** in any suitable direction. Semiconductor plug **414** can function as part of the channel of a source-select transistor (e.g., the source-select transistor having SSG **310** in FIG. 3) of NAND memory string **410**. In some implementations, NAND memory string **410** further includes a channel plug **416** in the upper portion (e.g., at the upper end) of NAND memory string **410**. In some implementations, channel plug **416** can function as the channel of a drain select transistor (e.g., the drain select transistor having DSG **312** in FIG. 3) of NAND memory string **410**. As used herein, the upper end of a component (e.g., channel structure **412**) is the end farther away from substrate **402** in the z-direction, and the lower end of the component (e.g., channel structure **412**) is the end closer to substrate **402** in the z-direction when substrate **402** is positioned in the lowest plane of memory cell array **202**.

[0053] FIG. 4B illustrates a top view of part of memory cell array **202**, which includes a block **434** in which a plurality of NAND memory strings **410** are located, according to some implementations. Multi-pass programming may be performed to program the threshold voltages of memory cells in block **434** to higher data states. Block **434** may be an example of block **304** in memory cell array **202** illustrated in FIG. 3. As shown in FIG. 4B, in the x-y plane, block **434** is located between a pair of gate-line slits (GLSs) **432** in memory cell array **202**. One or more (e.g., a pair of) GLSs **432** may further divide block **434** into a plurality of fingers **436A** and **436B**. A source contact (not shown) structure may be located in each GLS **432** and electrically coupled to source line **314**. A DSG cut **428** may be located in the upper portion of block **434** and divide block **434** into a pair of fingers **436A** and **436B**. Each finger **436A/436B** may include a plurality of NAND memory strings **410** arranged in the x-direction and the y-direction. In some implementations, the source contact structure each includes an insulating spacer and a conductive material in the insulating spacer. The insulating spacer may include a suitable dielectric material such as silicon oxide, and the conductive material may include W, Co, Al, Cu, polysilicon, silicides, etc. In

some implementations, DSG cut **428** extends in the x-direction and includes a suitable dielectric material such as silicon oxide, silicon nitride, silicon oxynitride, or a combination thereof.

[0054] In some implementations, the same voltage is applied via a DSG line (e.g., DSG line **313**) onto DSGs (e.g., DSGs **312**) of NAND memory strings **410** in the same finger. In some implementations, the DSGs of NAND memory strings **410** in each finger can be separately controlled by applying a respective voltage via the respective DSG line. In a programming pass, memory cells (e.g., memory cells **306**) coupled to the same word line (e.g., word line **318**) in block **434** may be applied with the same programming voltage/pulse and verify voltages at the same time. In some implementations, the same voltage is applied via an SSG line (e.g., SSG line **315**) onto SSGs (e.g., SSGs **310**) of NAND memory strings **410** in block **434**. In some implementations, each NAND memory string **410** is applied with a respective voltage via the respective bit line (e.g., bit line **316**). To perform the multi-pass programming on NAND memory strings **410** in block **434**, control logic **212** may control each peripheral circuit **302** to apply respective voltages. The details are illustrated as follows.

[0055] Referring back to FIG. 2, page buffer **204** can be configured to read and program data from and to memory cell array **202** according to the control of control logic **212**. In one example, page buffer **204** may store one page of program data (write data) to be programmed into one page **320** of memory cell array **202**. In another example, page buffer **204** also performs verify operations to ensure that the data has been properly programmed into memory cells **306** coupled to selected word lines **318**.

[0056] Row decoder/word line driver **208** can be configured to be controlled by control logic **212**. Row decoder/word line driver **208** may select/deselect a block **304** of memory cell array **202** and a word line **318** (page **320**) of the selected block **304**. Row decoder/word line driver **208** can be further configured to drive selected word line **318** using a word line voltage generated from voltage generator **210**. Row decoder/word line driver **208** can also be configured to select a finger of block **304**. Voltage generator **210** can be configured to be controlled by control logic **212** and generate the word line voltages (e.g., read voltage, program voltage, pass voltage, local voltage, and verification voltage) to be supplied to memory cell array **202**. Column decoder/bit line driver **206** can be configured to be controlled by control logic **212** and select one or more NAND memory strings **308** by applying bit line voltages generated from voltage generator **210**. For example, column decoder/bit line driver **206** may apply column signals for selecting a set of N bits of data from page buffer **204** to be outputted in a read operation.

[0057] Control logic **212** can be coupled to or deposited in each peripheral circuit **302** and configured to control operations of peripheral circuits **302**. For example, control logic **212** may control peripheral circuits **302** to perform multi-pass programming, which includes the disclosed NGS scheme in a non-last programming pass. Registers **214** can be coupled to control logic **212** and include status registers, command registers, and address registers for storing status information, command operation codes (OP codes), and command addresses for controlling the operations of each peripheral circuit **302**. Interface **216** can be coupled to control logic **212** and act as a control buffer to buffer and relay control commands received from a host (not shown) to

control logic 212 and status information received from control logic 212 to the host. Interface 216 can also be coupled to memory controller 106 and act as an I/O interface and a data buffer to buffer and relay the program data received from memory controller 106 to control logic 212.

[0058] FIG. 5A illustrates an exemplary multi-pass programming 500 applied on a selected word line (e.g., word line 318) of block 304 (or block 434), according to some implementations. FIG. 5B illustrates an exemplary program loop 506 including a NGS operation in a non-last programming pass 502 in multi-pass programming 500, according to some implementations. FIG. 5C illustrates an exemplary program loop 508 without a NGS operation in a last programming pass 504 in multi-pass programming 500 according to some implementations.

[0059] FIG. 5A illustrates an example of the voltages applied on memory cells coupled to a selected word line in multi-pass programming 500 via the selected word line, according to implementations of the present disclosure. Multi-pass programming 500 may include one or more non-last programming pass 502 and a last programming pass 504. For example, multi-pass programming 500 may be two-pass programming that includes a first programming/non-last pass 502 and a second/last programming pass 504. Each programming pass may include one or more program loops. For example, non-last programming pass 502 may include a plurality of program loops 506, and last programming pass 504 may include a plurality of program loops 508. Each program loop 506/508 may include a programming voltage/pulse applied by a programming operation and one or more verify voltages applied by a verify operation. The programming operation may apply programming voltage on the selected word line to program the memory cells in the selected word line into a data state. In some implementations, programming voltage increases stepwise in an amplitude in one or more program loops of a programming pass using a fixed or varying step size. In some implementations, an incremental step pulse programming (ISPP), in which programming voltage starts at an initial level and increases in a step in each successive program loop until a programming pass is completed. The verify operation may apply one or more verify voltages on the selected word line to test if the threshold voltages of the memory cells in the selected word lines have been programmed into the desired data states. It should be noted that the actual amplitudes of programming voltages and verify voltages are not limited by the implementations of the present disclosure. Although programming voltages in programming pass 504 are shown to be higher than programming voltages in programming pass 502 in FIG. 5A, depending on the operation, programming voltages in programming pass 504 may also be lower than or equal to programming voltages in programming pass 502.

[0060] FIG. 5B illustrates an example of voltages applied on the selected word line in program loop 506, according to implementations of the present disclosure. In some implementations, program loop 506 includes a programming operation 510, a NGS operation 512 following programming operation 510, and a verify operation 514 following NGS operation 512. In programming operation 510, a programming voltage V_{PGM1} may be applied on the selected word line to cause the threshold voltages of the memory cells coupled to the selected word line to be assigned to the higher data states. NGS operation 512 may be subsequently

enabled on all the memory cells coupled to the selected word line by applying a low voltage V_L on the selected word line. Details of NGS operation 512 is described as follows in FIGS. 6A and 6B. In some implementations, verify operation 514 is performed after NGS operation 512 to test if the threshold voltages of the memory cells assigned to the higher data state reach verify voltages V_{R1} (e.g., intermediate verify voltages) as shown in FIG. 5B.

[0061] FIG. 5C illustrates an example of voltages applied on the selected word line in program loop 508, according to implementations of the present disclosure. In some implementations, program loop 508 includes a programming operation 520 and a verify operation 524 following programming operation 520. No NGS operation is performed in any program loop 508 according to some implementations. In some implementations, NGS operation is inhibited on all memory cells in program loop 508, as shown in FIG. 5C. In programming operation 520, a programming voltage V_{PGM2} may be applied on the selected word line to cause the threshold voltages of the memory cells coupled to the selected word line to be assigned to the higher data states and/or have narrower distributions. In some implementations, verify operation 524 is performed after programming operation 520 to test if the threshold voltages of the memory cells assigned to the higher data state reach verify voltages V_{R2} (e.g., final verify voltages) as shown in FIG. 5C. In some implementations, although not shown, NGS operation is selectively enabled only on memory cells coupled to the selected word line and did not pass the respective verify operation immediately prior to the NGS operation.

[0062] Non-last programming pass 502 may or may not be the first programming pass in multi-pass programming 500. If non-last programming pass 502 is not the first programming pass, memory cells coupled to the selected word line may include memory cells passed the respective verify operations prior to non-last programming pass 502 and memory cells did not pass the respective verify operations prior to non-last programming pass 502. If non-last programming pass 502 is the first programming pass, all memory cells coupled to the selected word line may be treated as not passing the respective verify operations prior to non-last programming pass 502. According to the present disclosure, all memory cells coupled to the selected word line may undergo a NGS operation in non-last programming pass 502. However, in known multi-pass programming, in non-last programming pass 502, only memory cells that did not pass the respective verify operations prior to non-last programming pass 502 are selected to undergo respective NGS operations, while the NGS operations are inhibited in memory cells that passed the respective verify operations prior to non-last programming pass 502.

[0063] FIG. 6A illustrates a memory string 600 in an exemplary NGS operation, according to some implementations of the present disclosure. FIG. 6B illustrates an example of voltages applied on a selected word line in a program loop 506, according to some implementations of the present disclosure. For ease of illustration, FIGS. 6A and 6B are described together.

[0064] As shown in FIG. 6A, memory string 600 may include a plurality of memory cells arranged at respective cell depths, e.g., in the z-direction. Each of the memory cells may be coupled to a respective word line. For ease of illustration, a memory cell 602 is coupled to a selected word line 610 (e.g., 318), a memory cell 603 is coupled to an

unselected word line **611** adjacent to selected word line **610**, and other memory cells **608** are each coupled to an unselected word line **612**. Memory string **600** may also include a DSG transistor **604** at the upper end and an SSG transistor **606** at the lower end. DSG transistor **604** has a DSG (e.g., **312**) that is coupled to a DSG line **614**, and SSG transistor **606** has an SSG (e.g., **310**) that is coupled to an SSG line **616**. The DSG, the SSG, selected word line **610**, DSG line **614**, and SSG line **616** may be respective examples of DSG **312**, SSG **310**, selected word line **318**, DSG line **313**, and SSG line **315** illustrated in FIG. 3.

[0065] For each programming pass, **502** and **504**, word lines **612**, **611**, and **610** in the same block (e.g., block **304**) may be sequentially applied with respective voltages from bottom to top or from top to bottom in the z-direction, e.g., in a direction from SSG transistor **606** to DSG transistor **604** or vice versa. In an example, word lines **612**, **611**, and **610** are programmed from bottom to top in the z-direction, and word line **611** is located immediately below word line **610**. In some implementations, memory cell **603** is programmed before memory cell **602**, although the multi-pass programming may not be completed in memory cell **603** before started in memory cell **602**. When program loop **506** is performed on word line **610**, programming operation **510** may include the word line driver (e.g., **208** in FIG. 2) applying programming voltage V_{PGM} on word line **610**, i.e., the selected word line. Threshold voltages of memory cells coupled to word line **610** (e.g., memory cell **602**) may be programmed to higher data states. After programming operation **510**, NGS operation **512** may be enabled on some or all memory cells (details provided below) coupled to word line **610** (e.g., memory cell **602**). NGS operation **512** may include the word line driver applying low voltage V_L on word line **610** and applying a high voltage V_P on word lines **612**. Low voltage V_L may be V_{SS}/GND or a negative voltage applied on memory cells coupled to word line **610** (e.g., memory cell **602**). High voltage V_P may be a sufficiently high positive voltage that keeps memory cells **608** on during NGS operation **512**. In some implementations, V_P is higher than V_{DD} . After NGS operation **512**, verify operation **514** may be performed on memory cells coupled to word line **610** (e.g., memory cell **602**). Verify operation **514** may include the word line driver applying verify voltages V_{R1} on word line **610** to test if threshold voltages of any memory cells coupled to word line **610** have been successfully programmed into the higher data states.

[0066] NGS operation **512** may function as a “shallow etch” to remove at least some shallowly-trapped charges in all memory cells coupled to word line **610** (e.g., memory cell **602**). Specifically, to enable NGS operation **512** on memory cell **602**, memory string **600**, which memory cell **602** is located, is configured to be at a “floating” state and undergoes a potential boost, in which the potential of memory string **600** increases. In the present disclosure, to set memory string **600** to the “floating” state, DSG transistor **604** and SSG transistor **606** are both turned off. Specifically, the value of V_L is sufficiently low to ensure the value of the voltage on DSG line **614** minus the voltage on the bit line (e.g., **316**) is below the threshold voltage of DSG transistor **604**. DSG transistor **604** is thus turned off for both memory cells passed and did not pass the verify operations. As such, the NGS operation can be enabled on both memory cells passed and did not pass the verify operations. Different from a known NGS operation, which is only enabled on memory

cells that coupled to a selected word line and did not pass respective verify operations, NGS operation **512** is enabled on all memory cells coupled to a selected word line, e.g., word line **610**, when the word line **610** is being programmed in program loop **506**.

[0067] In the present disclosure, NGS operation **512** may be enabled on memory cells **602** and **603** at the same time. That is, although memory cell **603** may be programmed and/or may undergo a respective NGS operation prior to memory cell **602**, when NGS operation **512** is enabled on memory cell **602**, memory cell **603** may also undergo a respective NGS operation (e.g., **512**) at the same time as memory cell **602**. In some implementations, low voltage V_L may also be applied on word line **611** at the same time as word line **610**. Because memory string **600** is at the “floating” state, memory cell **603** may also undergo a shallow etch to further remove at least some shallowly-trapped charges in memory cell **603**. In some implementations, at least all memory cells coupled to word lines **610** and **611** and in the same finger undergo a NGS operation at the same time.

[0068] Referring back to FIG. 4B, as an example, memory string **600** may be located in finger **436B**. In some implementations, the same voltage is applied on the DSG transistors of all NAND memory strings **410** in the same finger, e.g., **436A** or **436B**. Memory cell **602** may or may not pass a respective verify operation immediately prior to the NGS operation **512**. If memory cell **602** passed the verify operation, in some implementations, to enable NGS operation **512** on memory cells **602** and **603**, memory string **600** is set to be “floating” by applying a turn-off voltage on DSG transistor **604** via DSG line **614** of the respective finger, applying a turn-off voltage on SSG transistor **606** via SSG line **616** of the respective finger, and applying a low voltage on the bit line (not shown) coupled to memory string **600**. If memory cell **602** did not pass the verify operation, in some implementations, to enable NGS operation **512** on memory cells **602** and **603**, memory string **600** is set to be “floating” by applying a turn-off voltage on DSG transistor **604** via DSG line **614** of the respective finger, applying a turn-off voltage on SSG transistor **606** via SSG line **616** of the respective finger, and applying a high voltage on the bit line (not shown) coupled to memory string **600**. That is, even if finger **436B** includes memory cells coupled to word line **610** and did not pass a respective verify operation immediately prior to the NGS operation **512** when word line **610** is selected for programming, DSG transistors **604** of all the memory strings in finger **436B** are turned off to enable NGS operations **512** in at least some memory cells coupled to word lines **610** and **611** (e.g., including memory cells **602** and **603**). In some implementations, a turn-off voltage includes a low voltage or a negative voltage, and a turn-on voltage includes a positive voltage. In some implementations, the turn-off voltage is V_{SS}/GND , and the turn-on voltage is V_{DD} . Meanwhile, low voltage V_L may be applied on memory cells **602** and **603** via word lines **610** and **611**, respectively, and high voltage V_P may be applied on memory cells **608** via word lines **612**. In some implementations, low voltage V_L includes one of V_{SS} and a negative voltage, and high voltage V_P includes a positive voltage higher than V_{DD} .

[0069] As shown in FIGS. 6A and 4B, memory cells **602** and **603** are in the same memory string **600** and same finger **436B**. For memory cells in different fingers, depending on the programming sequence, voltages applied to the DSG

transistors of the fingers can vary. FIGS. 7A-7C illustrate a word-line priority sequence and exemplary waveforms of voltages employed in the word-line priority sequence. 8A, 8B, and 7C illustrate a sawtooth sequence and exemplary waveforms of voltages employed in the sawtooth sequence.

[0070] FIG. 7A illustrates a word-line priority sequence in which non-last programming pass 502 and last programming pass 504 are performed. FIG. 7B illustrates exemplary waveforms of voltages applied on certain elements of memory string 600 in NGS operation 512 in program loop 506, according to some implementations. FIG. 7C illustrates waveforms of voltages applied on certain elements of memory string 600 in a NGS operation in program loop 508, according to some implementations. In various implementations, voltages shown in FIG. 7B are applied in a non-last programming pass, and voltages shown in FIG. 7C can be applied in a non-last programming pass or the last programming pass. In some implementations, NGS operations are inhibited in program loop 508, as referring back to FIG. 5C and related description.

[0071] As shown in FIG. 7A, the word-line priority sequence includes a sequence in which memory cells in adjacent fingers of a single row are programmed sequentially, e.g., immediately one after another, and the adjacent rows of memory cells are programmed in an interleaved manner. In FIG. 7A, “Finger 0”-“Finger 5” represent six fingers arranged in a memory device. Finger 0 and Finger 1 can be examples of fingers 436A and 436B, respectively of memory cell array. “WL #” represents the order number of the word lines. For example, WL0 represents the word line at the bottom (e.g., 0th word line, immediately above the SSGs), WL1 represents the word line (e.g., 1st word line) immediately above the 0th word line, WL2 represents the word line (e.g., 2nd word line) immediately above the 1st word line, . . . , WL64 represents the word line at the top (e.g., 63rd word line, immediately below the DSGs). In some implementations, the word lines are programmed from the 0th word line to the 1st word line. As an example, the multi-pass programming is a two-pass programming, having a first-pass programming (e.g., the non-last programming pass) and the second-pass programming (e.g., the last programming pass). Memory cells in Fingers 0-Finger 6 each undergoes a respective first-pass programming and a respective second-pass programming. In FIG. 7A, “1st” represents the order number of the first-pass programming, and “2nd” represents the order number of the second-pass programming.

[0072] In some implementations, the 0th row of memory cells, i.e., the memory cells coupled to the 0th word line are sequentially programmed from Finger 0 to Finger 5 to undergo the first-pass programming (e.g., 502). The sequence of the fingers being programmed is shown as order numbers 0-5. The 1st row of memory cells, i.e., the memory cells coupled to the 1st word line are then sequentially programmed from Finger 0 to Finger 5 to undergo the first-pass programming. The sequence of the fingers being programmed is shown as order numbers 6-11. The 1st row of memory cells are then sequentially programmed from Finger 0 to Finger 5 to undergo the second-pass programming (e.g., 504). The sequence of the fingers being programmed is shown as order numbers 12-17. The 2nd row of memory cells, i.e., the memory cells coupled to the 2nd word line are then sequentially programmed from Finger 0 to Finger 5 to undergo the first-pass programming (e.g., 502). The

sequence of the fingers being programmed is shown as order numbers 18-23. The 1st row of memory cells are then sequentially programmed from Finger 0 to Finger 5 to undergo the second-pass programming. The sequence of the fingers being programmed is shown as order numbers 24-29. The 3rd row of memory cells, i.e., the memory cells coupled to the 3rd word line are then sequentially programmed from Finger 0 to Finger 5 to undergo the first-pass programming. The sequence of the fingers being programmed is shown as order numbers 30-35. The 2nd row of memory cells are then sequentially programmed from Finger 0 to Finger 5 to undergo the second-pass programming. The sequence of the fingers being programmed is shown as order numbers 36-41. The memory cells coupled to the rest of the word lines may be programmed repeatedly following the word-line priority sequence, as described above, until the memory cells coupled to the 63rd word line undergo the second-pass programming.

[0073] As an example, 2nd word line may be the selected word line, similar to 610, and the memory cells, in Finger 0 to Finger 5, coupled to the 2nd word line may be the selected row of memory cells. The 1st word line may be the unselected word line similar to 611. When the selected row of memory cells are undergoing the first-pass programming, all the memory cells in the row coupled to the 1st word line have already undergone the first-pass programming but none have undergone the second-pass programming. For example, the memory cells in Finger 0 and coupled to the 2nd word line may first undergo a first-pass programming (in order number 18), the memory cells in Finger 1 and coupled to the 2nd word line may then undergo a first-pass programming (in order number 19), the memory cells in Finger 0 and coupled to the 1st word line may then undergo a second-pass programming (in order number 24), the memory cells in Finger 1 and coupled to the 1st word line may then undergo a second-pass programming (in order number 25), the memory cells in Finger 0 and coupled to the 2nd word line may then undergo a second-pass programming (in order number 36), and the memory cells in Finger 1 and coupled to the 2nd word line may then undergo a second-pass programming (in order number 37). That is, when the selected row of memory cells are undergoing the first-pass programming, the unselected row of memory cells immediately below the selected row have not undergone a second-pass programming. In some implementations, when memory cells coupled to the 2nd word line are undergoing a NGS operation, memory cells coupled to the 1st word line also undergo a NGS at the same time.

[0074] FIGS. 7B and 7C show waveforms of voltages applied on DSG line 614 and word lines 610, 611, and 612, in a first-pass programming and a second-pass programming. The NGS operations may be enabled in phases 700 and 701, respectively. In some implementations, DSG line 614 and word lines 610, 611, and 612 are ramped from initial voltages to respective voltages in phase 700/701 such that the NGS operations can be enabled. WLn represents the selected word line that is being programmed. WLn+1 represents the word line immediately above WLn in the z-direction. WL(above) represents all other word lines above WLn+1. WLn-1 represents the word line immediately below WLn in the z-direction, e.g., the unselected word line according to the examples in FIG. 6A. WL(below) represents all other word lines below WLn-1. DSG(sel) represents the waveform of voltages applied on DSG of a finger

having memory cells coupled to WL_n and not passed a respective verify operation immediately prior to the NGS operation. DSG (unsel) represents the waveform of voltages applied on DSG of a finger having memory cells coupled to WL_n and all passed a respective verify operation immediately prior to the NGS operation.

[0075] As shown in FIG. 7B, in phase 700, WL_n (e.g., 610) is being programmed and is applied with a low voltage. DSG line 614 may be applied with a low voltage such that DSG transistors of all memory strings in the finger may be turned off. In some implementations, the DSG transistors of all fingers (e.g., Finger 0-Finger 5) coupled to WL_n are turned off. In some implementations, the low voltage is V_{SS}/GND . In the meantime, other word lines 612 above and below WL_n and WL_n-1 (e.g., WL(above), WL_n+1, WL(below)) are each applied with a high voltage. In some implementations, other word lines are applied with a positive voltage of V_P . In some implementations, V_P is higher than V_{DD} .

[0076] Different from NGS operation 512, the NGS operation illustrated in FIG. 7C may be enabled only on memory cells coupled to WL_n and did not pass the respective verify operations immediately prior to the NGS operation. For example, if memory cell 602 did not pass the verify operation, DSG line 614 may be applied with a voltage of $V_{DSG_P_L}$; and if memory cell 602 passed the verify operation, DSG line 614 may be applied with a voltage of $V_{DSG_P_H}$. In some implementations, $V_{DSG_P_L}$ and $V_{DSG_P_H}$ are each a positive voltage, and $V_{DSG_P_H}$ is higher than $V_{DSG_P_L}$. As described above, in the NGS operation, the bit line of the memory string having memory cells coupled with WL_n and did not pass the verify operation may be applied with a high voltage, e.g., V_{DD} ; and the bit line of the memory string having memory cells in the selected word line and all passed the verify operation may be applied with a low voltage, e.g., V_{SS} . The value of $V_{DSG_P_L}$ minus V_{DD} is lower than the threshold voltage of the DSG transistor such that the DSG transistor is turned off, enabling the NGS operation on memory cells coupled with word line 610 and did not pass the respective verify operations. The value of $V_{DSG_P_H}$ minus V_{DD} is higher than the threshold voltage of the DSG transistor such that the DSG transistor is turned on, inhibiting the NGS operation on memory cells coupled with word line 610 and passed the respective verify operations.

[0077] FIG. 8A illustrates a sawtooth sequence in which non-last programming pass 502 and last programming pass 504 are performed. FIG. 8B illustrates exemplary waveforms of voltages applied on certain elements of memory string 600 in NGS operation 512 in program loop 506, according to some implementations. A NGS operation in program loop 508 may include the same waveforms of voltages as shown in FIG. 7C and the detailed description is not repeated herein. In various implementations, voltages shown in FIG. 8B are applied in a non-last programming pass, and voltages shown in FIG. 7C can be applied in a non-last programming pass or the last programming pass. In some implementations, NGS operations are inhibited in program loop 508, as referring back to FIG. 5C and related description.

[0078] As shown in FIG. 8A, the sawtooth sequence includes a sequence in which memory cells in adjacent rows are programmed sequentially, e.g., immediately one after another. In some implementations, the 0th row of memory cells, i.e., the memory cells coupled to the 0th word line are

sequentially programmed from Finger 0 to Finger 5 to undergo the first-pass programming (e.g., 502). The sequence of the fingers being programmed is shown as order numbers 0-5. The 1st row of memory cells in Finger 0, i.e., the memory cells coupled to the 1st word line and in Finger 0, then undergo a first-pass programming. The 0th row of memory cells in Finger 1, i.e., the memory cells coupled to the 0th word line and in Finger 1, then undergo a second-pass programming. The 1st row of memory cells in Finger 1, i.e., the memory cells coupled to the 1st word line and in Finger 1, then undergo a first-pass programming. The 0th row of memory cells in Finger 2, i.e., the memory cells coupled to the 0th word line and in Finger 2, then undergo a second-pass programming. The sequence of the fingers being programmed is shown as order numbers 6-9. The rest of the memory cells may be programmed repeatedly following the sawtooth priority sequence, as described above, until the memory cells coupled to the 63rd word line undergo the second-pass programming.

[0079] As an example, 2nd word line may be the selected word line, similar to 610, and the memory cells, in Finger 0 to Finger 5, coupled to the 2nd word line may be the selected row of memory cells. The 1st word line may be the unselected word line similar to 611. When the memory cells in the selected row in a finger are undergoing the first-pass programming, the memory cells in the unselected row in other fingers that have been programmed prior to the finger have already undergone the second-pass programming. For example, the memory cells in Finger 0 and coupled to the 2nd word line may first undergo a first-pass programming (in order number 18), the memory cells in Finger 0 and coupled to the 1st word line may then undergo a second-pass programming (in order number 19), the memory cells in Finger 0 and coupled to the 2nd word line may then undergo a first-pass programming (in order number 20), and the memory cells in Finger 2 and coupled to the 1st word line may then undergo a second-pass programming (in order number 21), the memory cells in Finger 0 and coupled to the 2nd word line may then undergo a second-pass programming (in order number 31), and the memory cells in Finger 1 and coupled to the 2nd word line may then undergo a second-pass programming (in order number 33). That is, when the selected row of memory cells are undergoing the first-pass programming, the memory cells in the unselected row immediately below the selected row may or may not have undergone a second-pass programming. In some implementations, when memory cells in the selected row and in one finger (e.g., Finger 1) is undergoing a first-pass programming, the memory cells in the unselected row in another finger (e.g., Finger 0) that are programmed prior to finger may have undergone a second-pass programming. The memory cells in the unselected row in the rest of the fingers (e.g., Fingers 2-5) have not undergone a second-pass programming. Thus, the memory cells in the unselected row and have undergone the second-pass programming may not undergo a NGS operation at the same time with the memory cells in the selected row.

[0080] In some implementations, for memory cells in the selected row and unselected row, only the memory cells in the selected fingers can undergo a NGS operation at the same. The selected finger may include the fingers having memory cells, in the selected and unselected rows, that did not pass the respective verify operations prior to the NGS operation. In some implementations, the selected fingers

may also include the fingers having memory cells in the selected and unselected rows and have not undergone a second-pass programming. The memory cells in the selected and unselected rows and in the unselected fingers may not undergo a NGS operation at the same time. In some implementations, the unselected fingers include the fingers having memory cells, in the selected and unselected rows, that have undergone the second-pass programming. In some implementations, in an unselected finger, all the memory cells in the selected and unselected rows have passed the respective verify operations prior to the NGS operation.

[0081] As an example, when memory cells coupled to the 2^{nd} word line and in Finger 1 are undergoing the first-pass programming, Finger 1 may be a selected finger. Memory cells coupled to the 1^{st} word line and in Finger 0 have undergone the second-pass programming. Finger 0 may be an unselected finger. In some implementations, Finger 0 is a unselected finger if all memory cells in Finger 0 and coupled to the 1^{st} and 2^{nd} word lines passed the verify operations. Finger 0 is a selected finger if at least one memory cell in Finger 0 and coupled to the 1^{st} and 2^{nd} word lines did not pass the verify operations. In some implementations, Fingers 2-5 may each be a selected finger.

[0082] Different from NGS operation 512, the NGS operation illustrated in FIG. 8B may be enabled only on memory cells coupled to WLn and $WLn-1$ and in selected fingers. The NGS operation may be performed in phase 800. or example, if memory cell 602 is in a selected finger, DSG line 614 may be applied with a voltage of V_{SS} ; and if memory cell 602 is in an unselected finger, DSG line 614 may be applied with a voltage of $V_{DSG_P_H}$. In some implementations, $V_{DSG_P_H}$ is a positive voltage higher than V_{DD} . As described above, in the NGS operation, the bit line of the memory string having memory cells coupled with WLn and did not pass the verify operation may be applied with a high voltage, e.g., V_{DD} ; and the bit line of the memory string having memory cells in the selected word line and all passed the verify operation may be applied with a low voltage, e.g., V_{SS} . The value of V_{SS} minus V_{DD} is lower than the threshold voltage of the DSG transistor such that the DSG transistor is turned off, enabling the NGS operation on memory cells coupled with word lines 610 and 611 and in the selected finger. The value of $V_{DSG_P_H}$ minus V_{DD} is higher than the threshold voltage of the DSG transistor such that the DSG transistor is turned on, inhibiting the NGS operation on memory cells coupled with word lines 610 and 611 and in the unselected finger.

[0083] FIG. 9 is a flowchart of an exemplary method 900 for operating a memory device, according to some implementations of the present disclosure. Examples of the memory device depicted in FIG. 9 include memory devices 104 depicted in FIG. 1A. For ease of illustration, FIG. 9 may be described in view of operations illustrated in FIGS. 3, 5A-5C, 6A, 6B, 7A-7C, 8A, and 8B. It is understood that the operations shown in method 900 are not exhaustive and that other operations can be performed as well before, after, or between any of the illustrated operations. Further, some of the operations may be performed simultaneously, or in a different order than shown in FIG. 9. In some implementations, method 900 is performed by peripheral circuits 302. Specifically, the word line driver (e.g., 208) may be configured to apply voltages on the word lines, the DSG line, and the SSG line, and bit line driver (e.g., 206) may be configured to apply voltages on the bit lines.

[0084] Referring to FIG. 9, method 900 starts at operation 902, in which a non-last programming pass is performed on a selected row of memory cells coupled to a selected word line. The non-last programming pass includes one or more program loops. At least one of the program loops includes a programming operation, a NGS operation after the programming operation, and a verify operation after the NGS operation. The NGS operation may be performed on the selected row of memory cells and an unselected row of memory cells adjacent to the selected row.

[0085] Referring back to FIGS. 5A-5C, 6A, 6B, 7A-7C, 8A, and 8B, a non-last programming pass, e.g., 502, may be performed on a selected row of memory cells coupled to a selected word line, e.g., 610/ WLn . The non-last programming pass may include one or more program loops, e.g., 506. At least one of the program loops includes a programming operation (e.g., 510), a NGS operation (e.g., 512) after the programming operation, and a verify operation (e.g., 514) after the NGS operation. The programming operation is first performed by applying a program voltage/pulse (e.g., V_{PGM}) on the selected word line. The NGS operation may be enabled on some or all memory cells in the selected row in one or more program loops 506 (e.g., each program loop 506). At the same time, the NGS operation may also be enabled in some or all memory cells in an unselected row adjacent to the selected row. To enable the NGS operation, DSGs (e.g., 614) in some fingers that include the memory cells coupled to the selected word line and the unselected word line are each applied respective voltages, as illustrated in FIGS. 7B and 8A. For a word-line priority sequence, DSGs of all fingers are applied with a low voltage, e.g., V_{SS} . For a sawtooth sequence, DSGs of selected fingers are applied with a low voltage, e.g., V_{SS} , and DSGs of unselected fingers are applied with a high voltage, e.g., $V_{DSG_P_H}$. Bit lines of memory strings having memory cells not passed the verify operation and passed the verify operation are respectively applied with a high voltage (e.g., V_{DD}) and a low voltage (V_{SS}). The SSGs (e.g., 616) in the fingers are applied with a low voltage, e.g., V_{SS} . In the meantime, a low voltage, GND or negative voltage, is applied on the selected word line and the unselected word line, and a positive voltage is applied on the word lines above and below the selected and unselected word line, as illustrated in FIGS. 6B, 7B, and 8A. For a word-line priority sequence, all memory cells coupled with the selected word line and the unselected word line can undergo a NGS operation at the same time. For a sawtooth sequence, only memory cells coupled with the selected word line and the unselected word line and are in the selected fingers can undergo a NGS operation at the same time. The verify operation may be performed on the memory cells coupled to the selected word line after the NGS operation by applying one or more verify voltages (e.g., V_{R1}) on the selected word line.

[0086] In some implementations, the NGS operation is enabled in each program loop in the non-last programming pass. In some implementations, if the program loop is the first program loop, e.g., before any verify operations is performed, each memory cells coupled to the selected word line is treated as a memory cell that did not pass a respective verify operation prior to the NGS operation.

[0087] Referring back to FIG. 9, method 900 proceeds to operation 904, in which the last programming pass is performed on the selected word line. The last programming pass includes one or more program loops. The program

loops may not include any NGS operations or include NGS operations enabled only on memory cells that did not pass respective verify operations immediately prior to the NGS operations.

[0088] Referring back to FIGS. 5A-5C, 6A, 6B, 7A-7C, 8A, and 8B, a last programming pass, e.g., 504, may be performed on the selected word line, e.g., 610/WLn. The last programming pass may include one or more program loops, e.g., 508. Different from the program loop in the non-last programming pass, the programming loop may not include any NGS operations on any memory cells or may include NGS operations enabled only on memory cells that did not pass respective verify operations immediately prior to the NGS operations. In some implementations, the NGS operations are not enabled on memory cells that passed the verify operations. In some implementations, NGS operation is inhibited between the programming operation (e.g., 520) and the following verify operation (524), as shown in FIG. 5C. In some implementations, a NGS operation is enabled between the programming operation and the following verify operation, and is only on memory cells coupled to the selected word line and did not pass respective verify operations immediately prior to the NGS operations. The NGS operation may be enabled in one or more program loops 508. The programming operations and the verify operation may be referred to the description of FIG. 5C and the detailed descriptions are not repeated herein. To inhibit the NGS operation on the memory cells coupled to the selected word line and passed the verify operations, DSGs (e.g., 614) in fingers that include these memory cells are each applied with a low positive voltage (e.g., $V_{DSG_P_L}$), as illustrated in FIG. 7C. To enable the NGS operation on the memory cells coupled to the selected word line and did not pass the verify operations, DSGs (e.g., 614) in fingers that include these memory cells are each applied with a high positive voltage (e.g., $V_{DSG_P_H}$), as illustrated in FIG. 7C. Bit lines of memory strings having memory cells not passed the verify operation and passed the verify operation are respectively applied with a high voltage (e.g., V_{DD}) and a low voltage (e.g., V_{SS}). The SSGs (e.g., 616) in the fingers are applied with a low voltage and are turned off. In the meantime, a low voltage, e.g., negative or GND voltage, is applied on the selected word line, and a positive voltage is applied on the word lines above and below the selected word line, as illustrated in FIGS. 6B, 7B, and 8A. The verify operation may be performed on the memory cells coupled to the selected word line after the NGS operation by applying one or more verify voltages (e.g., V_{R2}) on the selected word line. In some implementations, operation 904 is performed by peripheral circuits 302. It should be noted that, in various implementations, the verify operations (e.g., 514 and/or 524) may not be performed in all program loops.

[0089] Some aspects of the present disclosure provide a memory device. The memory device includes an array of memory cells arranged in a plurality of rows, a plurality of word lines respectively coupled to the plurality of rows of the memory cells, and a peripheral circuit coupled to the word lines and configured to perform multi-pass programming on a selected row of memory cells coupled to a selected word line of the word lines. The multi-pass programming includes a plurality of programming passes. Each of the programming passes includes a programming operation and a verify operation. To perform the multi-pass programming, the peripheral circuit is configured to, in a

non-last programming pass of memory cells, perform a NGS operation on a memory cell in the selected row of memory cells between the programming operation and the verify operation; and at a same time, perform a NGS operation on a memory cell in an unselected row of memory cells coupled to an unselected word line of the word lines. The unselected word line is adjacent to the selected word line.

[0090] In some implementations, the peripheral circuit includes a word line driver coupled to the plurality of word lines. To perform the NGS operations on the selected row and the unselected row of memory cells, the word line driver is configured to apply one of a negative voltage or a GND voltage respectively on the selected word line and the unselected word line.

[0091] In some implementations, to perform the NGS operations on the selected row and the unselected row of memory cells, the word line driver is further configured to apply a positive voltage on the rest of the word lines.

[0092] In some implementations, the memory device further includes a plurality of bit lines. The array of memory cells includes a plurality of strings coupled to the plurality of bit lines. The strings each includes a SSG transistor. The memory cells in the selected row are in the plurality of strings, respectively. To perform the respective NGS operation on the selected row of memory cells and the unselected row of memory cells, the peripheral circuit is further configured to turn off the SSG transistor of each of the strings.

[0093] In some implementations, in response to the row of memory cells having a memory cell not passing a respective verify operation immediately prior to the NGS operation, a bit line voltage is a positive voltage. In some implementations, in response to the row of memory cells including a memory cell passing a respective verify operation immediately prior to the NGS operation, the bit line voltage is a GND voltage.

[0094] In some implementations, the plurality of strings are arranged in a plurality of fingers, and the multi-pass programming includes sequence. The sequence includes performing the non-last programming pass is on a first memory cell of the selected row in a first finger of the fingers, performing the non-last programming pass on a second memory cell of the selected row in a second finger of the fingers immediately after the non-last programming pass on the first memory cell, and performing a last programming pass on a third memory cell of the unselected row in the first finger after the non-last programming pass on the second memory cell.

[0095] In some implementations, the NGS operations are performed on each memory cells in the selected and unselected rows.

[0096] In some implementations, the strings each includes a DSG transistor. In some implementations, to perform the respective NGS operation on the selected row and the unselected row of memory cells, the peripheral circuit is further configured to turn off the DSG transistor of each of the strings in the plurality of fingers.

[0097] In some implementations, the peripheral circuit includes a bit line driver coupled to the plurality of bit lines and the word line driver is coupled to the DSG transistor via a DSG line. In some implementations, to turn off the DSG transistor of the first and second the strings, the bit line driver is configured to apply a bit line voltage respectively on each of the strings. In some implementations, the word line driver is configured to apply, respectively on each of the

strings, a DSG voltage on the DSG transistor via the DSG line, a value of the DSG voltage minus the bit line voltage being lower than a threshold voltage of the DSG transistor.

[0098] In some implementations, the DSG voltage is a GND voltage.

[0099] In some implementations, the plurality of strings are arranged in a plurality of fingers, and the multi-pass programming includes a sequence. The sequence includes performing the non-last programming pass on a first memory cell of the selected row in a first finger of the fingers, performing a last programming pass on a second memory cell of the unselected row in the first finger immediately after the non-last programming pass on the first memory cell, and performing the non-last programming pass on a third memory cell of the selected row in a second finger of the fingers immediately after the last programming pass on the second memory cell.

[0100] In some implementations, in the selected and unselected rows, the NGS operations are performed on memory cells in a selected finger in response to (i) the last programming pass not being performed or (ii) the last programming pass being performed and the selected finger including at least one memory cell not passed the respective verify operation. In some implementations, the NGS operations are inhibited on memory cells in an unselected finger in response to (i) the last programming pass being performed and (ii) the memory cells all passed the respective verify operation.

[0101] In some implementations, the strings each includes a DSG transistor. In some implementations, to perform the respective NGS operation on the selected row and the unselected row of memory cells, the peripheral circuit is further configured to turn off the DSG transistors of strings in the selected finger in response to the last programming pass is not performed on the selected finger; and turn on the DSG transistors of strings in the unselected finger in response to the last programming pass is performed on the unselected finger.

[0102] In some implementations, the peripheral circuit includes a bit line driver coupled to the plurality of bit lines and the word line driver is coupled to the DSG transistor via a DSG line. In some implementations, the bit line driver is configured to apply, of each of the strings, a bit line voltage on the respective bit line. In some implementations, the word line driver is configured to apply, of each of the strings, a DSG voltage on the DSG transistor via the DSG line. In some implementations, to turn off the DSG transistor of each of the strings, a value of the DSG voltage minus the bit line voltage being lower than a threshold voltage of the DSG transistor. In some implementations, to turn on the DSG transistor of each of the strings, a value of the DSG voltage minus the bit line voltage being higher than the threshold voltage of the DSG transistor.

[0103] In some implementations, the DSG voltage applied on the selected finger is a GND voltage, and the DSG voltage applied on the unselected finger is a positive voltage.

[0104] In some implementations, the peripheral circuit includes an SSG line coupled to the SSG transistor of each of the strings and a source driver coupled to the SSG line. In some implementations, the source driver is configured to apply a GND voltage on the SSG line.

[0105] In some implementations, to perform the multi-pass programming, the peripheral circuit is configured to, in a last programming pass, in response to one of the memory

cells in the selected row or the unselected row passing a respective verify operation immediately prior to the last programming pass, inhibit a respective NGS operation on the one of the memory cells. In some implementations, to perform the multi-pass programming, the peripheral circuit is configured to, in a last programming pass, in response to another one of the memory cells in the selected row or the unselected row not passing a respective verify operation immediately prior to the last programming pass, perform a respective NGS operation on the other one of the memory cells.

[0106] In some implementations, to perform the multi-pass programming, the peripheral circuit is configured to, in the last programming pass, inhibit a respective NGS on each of the memory cells in the selected row and the unselected row of memory cells.

[0107] In some implementations, the NGS operation is performed between a respective programming operation and a respective verify operation.

[0108] In some implementations, the non-last programming pass includes a plurality of programming operations and a plurality of verify operations. The NGS operation is performed after each of the programming operations and before a respective verify operation.

[0109] In some implementations, the memory device is a 3D NAND Flash memory device.

[0110] Some aspects of the present disclosure provide a method for operating a memory device having an array of memory cells arranged in a plurality of rows and a plurality of word lines respectively coupled to the plurality of rows of the memory cells. The method includes performing multi-pass programming on a selected row of memory cells coupled to a selected word line of the word lines. The multi-pass programming includes a plurality of programming passes. Each of the programming passes includes a programming operation and a verify operation. Performing the multi-pass programming includes, in a non-last programming pass of memory cells, perform a NGS operation on a memory cell in the selected row of memory cells between the programming operation and the verify operation. Performing the multi-pass programming also includes, at a same time, perform a NGS operation on a memory cell in an unselected row of memory cells coupled to an unselected word line of the word lines, the unselected word line being adjacent to the selected word line.

[0111] In some implementations, performing the NGS operations on the selected row and the unselected row of memory cells includes applying one of a negative voltage or a GND voltage respectively on the selected word line and the unselected word line.

[0112] In some implementations, performing the NGS operations on the selected row and the unselected row of memory cells further includes applying a positive voltage on the rest of the word lines.

[0113] In some implementations, the memory device includes a plurality of bit lines, the array of memory cells including a plurality of strings coupled to the plurality of bit lines. The strings each includes a SSG transistor. The memory cells in the selected row are in the plurality of strings, respectively. In some implementations, performing the respective NGS operation on the selected row of memory cells and the unselected row of memory cells includes turning off the SSG transistor of each of the strings.

[0114] In some implementations, the method further includes, in response to the row of memory cells having a memory cell not passing a respective verify operation immediately prior to the NGS operation, applying a positive voltage as a bit line voltage. In some implementations, the method further includes, in response to the row of memory cells including a memory cell passing a respective verify operation immediately prior to the NGS operation, applying a GND voltage as the bit line voltage.

[0115] In some implementations, the plurality of strings are arranged in a plurality of fingers, and the multi-pass programming includes a sequence. The sequence includes performing the non-last programming pass on a first memory cell of the selected row in a first finger of the fingers, performing the non-last programming pass on a second memory cell of the selected row in a second finger of the fingers immediately after the non-last programming pass on the first memory cell, and performing a last programming pass on a third memory cell of the unselected row in the first finger after the non-last programming pass on the second memory cell.

[0116] In some implementations, the method includes performing the NGS operations on each memory cells in the selected and unselected rows.

[0117] In some implementations, the strings each includes a DSG transistor. In some implementations, performing the respective NGS operation on the selected row and the unselected row of memory cells includes turning off the DSG transistor of each of the strings in the plurality of fingers.

[0118] In some implementations, the method includes applying a bit line voltage respectively on each of the strings. In some implementations, the method also includes applying, respectively on each of the strings, a DSG voltage on the DSG transistor via the DSG line. A value of the DSG voltage minus the bit line voltage is lower than a threshold voltage of the DSG transistor.

[0119] In some implementations, the DSG voltage is a GND voltage.

[0120] In some implementations, the plurality of strings are arranged in a plurality of fingers, and the multi-pass programming includes a sequence. The sequence includes performing the non-last programming pass on a first memory cell of the selected row in a first finger of the fingers, performing a last programming pass on a second memory cell of the unselected row in the first finger immediately after the non-last programming pass on the first memory cell, and performing the non-last programming pass on a third memory cell of the selected row in a second finger of the fingers immediately after the last programming pass on the second memory cell.

[0121] In some implementations, the method also includes, in the selected and unselected rows, performing the NGS operations on memory cells in a selected finger in response to (i) the last programming pass not being performed or (ii) the last programming pass being performed and the selected finger including at least one memory cell not passed the respective verify operation. In some implementations, the method also includes, in the selected and unselected rows, inhibiting the NGS operations on memory cells in an unselected finger in response to (i) the last programming pass being performed and (ii) the memory cells all passed the respective verify operation.

[0122] In some implementations, the strings each includes a DSG transistor. In some implementations, performing the respective NGS operation on the selected row and the unselected row of memory cells includes turning off the DSG transistors of strings in the selected finger in response to the last programming pass is not performed on the selected finger. In some implementations, performing the respective NGS operation on the selected row and the unselected row of memory cells also includes turning on the DSG transistors of strings in the unselected finger in response to the last programming pass is performed on the unselected finger.

[0123] In some implementations, the method includes applying, of each of the strings, a bit line voltage on the respective bit line. In some implementations, the method also includes applying, of each of the strings, a DSG voltage on the DSG transistor via the DSG line. In some implementations, the method further includes turning off the DSG transistor of each of the strings, a value of the DSG voltage minus the bit line voltage being lower than a threshold voltage of the DSG transistor. In some implementations, the method further includes turning on the DSG transistor of each of the strings, a value of the DSG voltage minus the bit line voltage being higher than the threshold voltage of the DSG transistor.

[0124] In some implementations, the method includes applying a GND voltage as the DSG voltage on the selected finger, and applying a positive voltage as the DSG voltage on the unselected finger.

[0125] In some implementations, the memory device includes an SSG line coupled to the SSG transistor of each of the strings, and the method includes applying a GND voltage on the SSG line.

[0126] In some implementations, performing the multi-pass programming includes, in a last programming pass, in response to one of the memory cells in the selected row or the unselected row passing a respective verify operation immediately prior to the last programming pass, inhibiting a respective NGS operation on the one of the memory cells. In some implementations, performing the multi-pass programming includes, in a last programming pass, in response to another one of the memory cells in the selected row or the unselected row not passing a respective verify operation immediately prior to the last programming pass, performing a respective NGS operation on the other one of the memory cells.

[0127] In some implementations, performing the multi-pass programming includes, in the last programming pass, inhibiting a respective NGS on each of the memory cells in the selected row and the unselected row of memory cells.

[0128] In some implementations, the method includes performing the NGS operation between a respective programming operation and a respective verify operation.

[0129] In some implementations, the non-last programming pass includes a plurality of programming operations and a plurality of verify operations, and the method includes performing the NGS operation after each of the programming operations and before a respective verify operation.

[0130] Some aspects of the present disclosure further provide a system. The system includes a memory device configured to store data and a memory controller coupled to the memory device and configured to control the memory device. The memory device includes an array of memory cells arranged in a plurality of rows, a plurality of word lines

respectively coupled to the plurality of rows of the memory cells, and a peripheral circuit coupled to the word lines and configured to perform multi-pass programming on a selected row of memory cells coupled to a selected word line of the word lines. The multi-pass programming includes a plurality of programming passes. Each of the programming passes includes a programming operation and a verify operation. To perform the multi-pass programming, the peripheral circuit is configured to, in a non-last programming pass of memory cells, perform a NGS operation on a memory cell in the selected row of memory cells between the programming operation and the verify operation. To perform the multi-pass programming, the peripheral circuit is configured to, at a same time, perform a NGS operation on a memory cell in an unselected row of memory cells coupled to an unselected word line of the word lines, the unselected word line being adjacent to the selected word line.

[0131] In some implementations, the system further includes a host coupled to the memory controller and configured to send or receive the data.

[0132] In some implementations, the memory device is a 3D NAND Flash memory device.

[0133] In some implementations, the peripheral circuit includes a word line driver coupled to the plurality of word lines, and wherein to perform the NGS operations on the selected row and the unselected row of memory cells, the word line driver is configured to apply one of a negative voltage or a ground (GND) voltage respectively on the selected word line and the unselected word line.

[0134] In some implementations, to perform the multi-pass programming, the peripheral circuit is configured to, in a last programming pass, in response to one of the memory cells in the selected row or the unselected row passing a respective verify operation immediately prior to the last programming pass, inhibit a respective NGS operation on the one of the memory cells. In some implementations, to perform the multi-pass programming, the peripheral circuit is also configured to, in response to another one of the memory cells in the selected row or the unselected row not passing a respective verify operation immediately prior to the last programming pass, perform a respective NGS operation on the other one of the memory cells.

[0135] The foregoing description of the specific implementations can be readily modified and/or adapted for various applications. Therefore, such adaptations and modifications are intended to be within the meaning and range of equivalents of the disclosed implementations, based on the teaching and guidance presented herein.

[0136] The breadth and scope of the present disclosure should not be limited by any of the above-described exemplary implementations, but should be defined only in accordance with the following claims and their equivalents.

1. A memory device, comprising:

an array of memory cells arranged in a plurality of rows;
a plurality of word lines respectively coupled to the plurality of rows of the memory cells; and

a peripheral circuit coupled to the word lines and configured to perform multi-pass programming on a row of memory cells coupled to a word line of the plurality of word lines, the multi-pass programming comprising a plurality of programming passes, each of the programming passes comprising a programming operation and a verify operation, wherein, to perform the multi-pass

programming, the peripheral circuit is configured to, in a non-last programming pass of memory cells, perform, during a first time period, a negative gate stress (NGS) operation on a memory cell in a first row of memory cells coupled to a first word line, between the programming operation and the verify operation, wherein the first word line is selected during the first time period; and

during the first time period, perform a NGS operation on a memory cell in a second row of memory cells coupled to a second word line of the plurality of word lines, the second word line being unselected during the first time period, and vertically adjacent to the first word line.

2. The memory device of claim 1, wherein the peripheral circuit comprises a word line driver coupled to the plurality of word lines, and wherein to perform the NGS operations on the first row and the second row of memory cells, the word line driver is configured to apply one of a negative voltage or a ground (GND) voltage respectively on the first word line and the second word line.

3. The memory device of claim 2, wherein to perform the NGS operations on the first row and the second row of memory cells, the word line driver is further configured to apply a positive voltage on the rest of the plurality of word lines.

4. The memory device claim 1, further comprising a plurality of bit lines, wherein:

the array of memory cells comprises a plurality of strings coupled to the plurality of bit lines, the strings each comprising a source-select gate (SSG) transistor;

the memory cells in the first row are in the plurality of strings, respectively; and

to perform, during the first time period, the respective NGS operation on the first row of memory cells and the second row of memory cells, the peripheral circuit is further configured to turn off the SSG transistor of each of the strings.

5. The memory device of claim 4, wherein,

in response to the row of memory cells comprising a memory cell not passing a respective verify operation immediately prior to the NGS operation, a bit line voltage is a positive voltage; and

in response to the row of memory cells comprising a memory cell passing a respective verify operation immediately prior to the NGS operation, the bit line voltage is a GND voltage.

6. The memory device of claim 5, wherein the plurality of strings are arranged in a plurality of fingers, and the multi-pass programming comprises a sequence comprising:

performing the non-last programming pass on a first memory cell of the first row in a first finger of the plurality of fingers, wherein the first row is selected;

performing the non-last programming pass on a second memory cell of the first row in a second finger of the plurality of fingers immediately after the non-last programming pass on the first memory cell; and

performing a last programming pass on a third memory cell of the second row in the first finger of the plurality of fingers after the non-last programming pass on the second memory cell.

7. The memory device of claim 6, wherein the NGS operations are performed on each memory cell in the first and second rows, wherein the first row is selected and the second row is unselected.

- 8.** The memory device of claim **6**, wherein the strings each comprise a drain-select gate (DSG) transistor; and
- to perform the respective NGS operation on the first row and the second row of memory cells, wherein the first row is selected and the second row is unselected, the peripheral circuit is further configured to turn off the DSG transistor of each of the strings in the plurality of fingers.
- 9.** The memory device of claim **8**, wherein the peripheral circuit comprises a bit line driver coupled to the plurality of bit lines and a word line driver is coupled to the DSG transistor via a DSG line, and wherein to turn off the DSG transistor of a first and a second string,
- the bit line driver is configured to apply a bit line voltage respectively on each of the strings; and
- the word line driver is configured to apply, respectively on each of the strings, a DSG voltage on the DSG transistor via the DSG line, a value of the DSG voltage minus the bit line voltage being lower than a threshold voltage of the DSG transistor.
- 10.** The memory device of claim **5**, wherein the plurality of strings are arranged in a plurality of fingers, and the multi-pass programming comprises a sequence comprising:
- performing the non-last programming pass on a first memory cell of the first row in a first finger of the plurality of fingers;
- performing a last programming pass on a second memory cell of the second row in the first finger of the plurality of fingers immediately after the non-last programming pass on the first memory cell; and
- performing the non-last programming pass on a third memory cell of the first row in a second finger of the plurality of fingers immediately after the last programming pass on the second memory cell.
- 11.** The memory device of claim **10**, wherein in the first and second rows,
- the NGS operations are performed on memory cells in a selected finger in response to (i) the last programming pass not being performed or (ii) the last programming pass being performed and the selected finger comprising at least one memory cell not having passed the respective verify operation; and
- the NGS operations are inhibited on memory cells in an unselected finger in response to (i) the last programming pass being performed and (ii) the memory cells all having passed the respective verify operation.
- 12.** The memory device of claim **10**, wherein the strings each comprise a drain-select gate (DSG) transistor; and
- to perform the respective NGS operation on the first row and the second row of memory cells, wherein the first row is selected and the second row is unselected, the peripheral circuit is further configured to:
- turn off the DSG transistors of strings in a selected finger of the plurality of fingers in response to the last programming pass is not performed on the selected finger; and
- turn on the DSG transistors of strings in an unselected finger in response to the last programming pass is performed on the unselected finger of the plurality of fingers.
- 13.** The memory device of claim **12**, wherein:
- the peripheral circuit comprises a bit line driver coupled to the plurality of bit lines and a word line driver is coupled to the DSG transistor via a DSG line;
- the bit line driver is configured to apply, to each of the strings, a bit line voltage on the respective bit line;
- the word line driver is configured to apply, to each of the strings, a DSG voltage on the DSG transistor via the DSG line;
- to turn off the DSG transistor of each of the strings, a value of the DSG voltage minus the bit line voltage being lower than a threshold voltage of the DSG transistor; and
- to turn on the DSG transistor of each of the strings, a value of the DSG voltage minus the bit line voltage being higher than the threshold voltage of the DSG transistor.
- 14.** The memory device of claim **1**, wherein, to perform the multi-pass programming, the peripheral circuit is configured to, in a last programming pass:
- in response to one of the memory cells in a first row or a second row passing a respective verify operation immediately prior to the last programming pass, inhibit a respective NGS operation on the one of the memory cells; and
- in response to another one of the memory cells in the a first row or a second row not passing a respective verify operation immediately prior to the last programming pass, perform a respective NGS operation on the other one of the memory cells.
- 15.** The memory device of claim **1**, wherein, to perform the multi-pass programming, the peripheral circuit is configured to, in the last programming pass, inhibit a respective NGS on each of the memory cells in the first row and the second row of memory cells.
- 16.** A method for operating a memory device comprising an array of memory cells arranged in a plurality of rows and a plurality of word lines respectively coupled to the plurality of rows of the memory cells, the method comprising:
- performing multi-pass programming on a first row of memory cells coupled to a first word line of the plurality of word lines, the multi-pass programming comprising a plurality of programming passes, each of the programming passes comprising a programming operation and a verify operation, wherein performing the multi-pass programming comprises,
- in a non-last programming pass of memory cells, perform a negative gate stress (NGS) operation on a memory cell in the first row of memory cells between the programming operation and the verify operation; and
- at a same time, perform a NGS operation on a memory cell in a second row of memory cells coupled to a second word line of the word lines, the second word line being adjacent to the first word line, wherein the first word line is selected and the second word line is unselected.
- 17.** The method of claim **16**, wherein performing the NGS operations on the first row and the second row of memory cells comprises applying one of a negative voltage or a ground (GND) voltage respectively on the first word line and the second word line, and the method further comprises:
- in response to the first row of memory cells comprising a memory cell not passing a respective verify operation immediately prior to the NGS operation, applying a positive voltage as a bit line voltage; and

in response to the first row of memory cells comprising a memory cell passing a respective verify operation immediately prior to the NGS operation, applying a GND voltage as the bit line voltage.

18. The method of claim **17**, wherein a plurality of strings are arranged in a plurality of fingers, and the multi-pass programming comprises a sequence comprising:

performing the non-last programming pass on a first memory cell of the first row in a first finger of the plurality of fingers;

performing the non-last programming pass on a second memory cell of the first row in a second finger of the plurality of fingers immediately after the non-last programming pass on the first memory cell; and

performing a last programming pass on a third memory cell of the second row in the first finger after the non-last programming pass on the second memory cell.

19. The method of claim **17**, wherein a plurality of strings are arranged in a plurality of fingers, and the multi-pass programming comprises a sequence comprising:

performing the non-last programming pass on a first memory cell of a first row in a first finger of the plurality of fingers;

performing a last programming pass on a second memory cell of a second row in the first finger of the plurality of fingers immediately after the non-last programming pass on the first memory cell; and

performing the non-last programming pass on a third memory cell of the first row in a second finger of the

plurality of fingers immediately after the last programming pass on the second memory cell.

20. A system, comprising:

a memory device configured to store data, the memory device comprising:

an array of memory cells arranged in a plurality of rows; a plurality of word lines respectively coupled to the plurality of rows of the memory cells; and

a peripheral circuit coupled to the word lines and configured to perform multi-pass programming on a selected row of memory cells coupled to a selected word line of the plurality of word lines, the multi-pass programming comprising a plurality of programming passes, each of the programming passes comprising a programming operation and a verify operation, wherein, to perform the multi-pass programming, the peripheral circuit is configured to, in a non-last programming pass of memory cells,

perform a negative gate stress (NGS) operation on a memory cell in the selected row of memory cells between the programming operation and the verify operation; and

at a same time, perform a NGS operation on a memory cell in an unselected row of memory cells coupled to an unselected word line of the plurality of word lines, the unselected word line being adjacent to the selected word line; and

a memory controller coupled to the memory device and configured to control the memory device.

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